

This item is the archived peer-reviewed author-version of:

Atomically engineered interfaces yield extraordinary electrostriction

Reference:

Zhang Haiwu, Pryds Nini, Park Dae-Sung, Gauquelin Nicolas, Santucci Simone, Christensen Dennis, V., Jannis Daen, Chezganov Dmitry, Rata Diana A., Insinga Andrea R.,- Atomically engineered interfaces yield extraordinary electrostriction
Nature - ISSN 1476-4687 - 609:7928(2022), p. 695-700
Full text (Publisher's DOI): <https://doi.org/10.1038/S41586-022-05073-6>
To cite this reference: <https://hdl.handle.net/10067/1905760151162165141>

1

2 **Atomically engineered interfaces yield extraordinary**

3 **electrostriction**

4 Haiwu Zhang^{1,7*}, Nini Pryds^{1,7*}, Dae-Sung Park², Nicolas Gauquelin³, Simone Santucci¹,
5 Dennis V. Christensen¹, Daen Jannis³, Dmitry Chezganov³, Diana A. Rata⁴, Andrea R.
6 Insinga¹, Ivano E. Castelli¹, Johan Verbeeck³, Igor Lubomirsky⁵, Paul Muralt⁶, Dragan
7 Damjanovic², and Vincenzo Esposito^{1*}

8 ¹Department of Energy Conversion and Storage, Technical University of Denmark, Fysikvej
9 309, 2800 Kgs. Lyngby, Denmark

10 ²Group for Ferroelectrics and Functional Oxides, Institute of Materials, Swiss Federal Institute
11 of Technology-EPFL, CH-1015 Lausanne, Switzerland

12 ³Electron Microscopy for Materials Science (EMAT), University of Antwerp, B-2020
13 Antwerpen, Belgium

14 ⁴Institut für Physik, Martin-Luther-Universität Halle-Wittenberg, 06120 Halle, Germany

15 ⁵Department of Materials and Interfaces, Weizmann Institute of Science, Rehovot 76100, Israel

16 ⁶Department of Materials, Swiss Federal Institute of Technology, 1015, Switzerland

17 ⁷ These authors contributed equally: H. Zhang, N. Pryds

18 *E-mail: haizh@dtu.dk; nipr@dtu.dk; vies@dtu.dk

19

20 **Electrostriction is a property of the dielectric materials whereby an applied electric**
21 **field induces a mechanical deformation proportional to the square of the electric**
22 **field. The magnitude of the effect is usually minuscule (less than 10^{-19} m²/V² for**
23 **simple oxides). However, symmetry-breaking phenomena at the interfaces can offer**

24 **an efficient strategy to design new properties.**^{1, 2} **Herein, we report an engineered**
25 **electrostrictive effect via the epitaxial deposition of alternating layers of Gd₂O₃-**
26 **doped CeO₂ and Er₂O₃-stabilized δ -Bi₂O₃ with atomically controlled interfaces on**
27 **NdGaO₃ substrates. The value of the electrostriction coefficient achieved is $2.38 \times$**
28 **$10^{-14} \text{ m}^2/\text{V}^2$, exceeding the best-known relaxor ferroelectrics by three orders of**
29 **magnitude. Our theoretical calculations indicate that the extraordinary**
30 **electrostriction arises from coherent strain imparted by the interfacial lattice**
31 **discontinuity. These artificial heterostructures open a new avenue for designing and**
32 **manipulating electrostrictive materials and devices for nano/micro actuation and**
33 **cutting-edge sensors.**

34

35 Materials that develop strains in response to an electric field have attracted substantial
36 attention over the past decades owing to their wide applications, including non-resonant
37 actuators, high-end transducers, artificial muscles, energy harvesting, and various
38 sensors.^{3, 4} Although piezoelectricity is limited to materials with a non-centrosymmetric
39 crystal structure, electrostriction is a property exhibited by all dielectrics, which produces
40 a high displacement accuracy in the absence of strain-field hysteresis and remnant
41 polarisation. Electrostrictors are characterised by a fourth rank tensor called
42 electrostriction coefficient (M_{ijmn} , here shortened as M_{xx}), which relates the induced strain
43 (ϵ_{ij}^*) to the electric field (E_n) via $\epsilon_{ij}^* = \sum_{n,m} M_{ijmn} E_n E_m$. The magnitude of M_{xx} is usually

44 low ($\ll 10^{-19} \text{ m}^2/\text{V}^2$) for simple oxides, such as MgO, TiO₂, and Y:ZrO₂.⁵ Relaxor
45 ferroelectrics and ferroelectric polymers are two archetypes of electrostrictive materials
46 which exhibit high electromechanical responses.^{5, 6} Lead-based relaxors exhibit a larger
47 electrostriction coefficient ($1.0 \times 10^{-17} \text{ m}^2/\text{V}^2$) and generate high saturation stress (up to
48 150 MPa).^{7, 8} Polymers also possess high electrostriction coefficients ($1.8 \times 10^{-18} \text{ m}^2/\text{V}^2$).
49 However, the stress delivered is approximately two orders of magnitude lower (2 MPa on
50 average).⁹ Recently, Gd₂O₃-doped CeO₂ (CGO) based electrostriction materials revealed
51 anomalously large electrostriction with the saturation stress exceeding 500 MPa.¹⁰⁻¹⁴ This
52 class of electrostrictors represents a promising lead-free alternative to ferroelectric
53 materials.

54 The integration and size reduction of nano/microelectronic devices impetus the
55 development of electrostrictors that can operate with low power consumption and long-
56 term stability. Heterostructure multilayers are a promising platform for the development
57 of next-generation nanoscale materials and properties, e.g., fast ionic conduction,¹⁵ metal-
58 to-insulator transitions,¹⁶ and ferroelectricity in paraelectric materials.¹⁷ Such properties
59 are associated with the complex yet tailorable interfacial properties, resulting in
60 ionic/electronic redistribution, symmetry breaking, and strain gradients.^{1, 2, 18} However,
61 the scaling effect associated with interface engineering of electrostriction materials
62 remains a fundamental question needed to be addressed.¹⁹⁻²³

63 Herein, we report a novel approach for engineering electrostriction through artificial
64 interfaces. Gd₂O₃-doped CeO₂ (CGO) and Er₂O₃-stabilized δ -Bi₂O₃ (ESB) were selected
65 to design multilayers as model material systems. The lattice mismatch between the CGO
66 and the ESB layers was used to tune the local interfacial distortions and amplify the
67 electrostriction. This strategy yields an electrostrictive enhancement of three orders of
68 magnitude compared to single-layered CGO films, resulting in the highest value (M_{xx}
69 $\sim 10^{-14}$ m²/V²) measured in any electrostrictive materials. This kind of artificial
70 electrostrictive heterostructures opens up new opportunities for developing high-
71 performance nano-/micro-electromechanical devices.

72 Ultrathin films were deposited using pulsed laser deposition (PLD). The heterostructures
73 contain alternating layers of gadolinium-doped ceria (Ce_{0.8}Gd_{0.2}O_{1.9}, CGO) and erbium-
74 stabilised bismuth oxide (Er_{0.4}Bi_{1.6}O₃, ESB) deposited on pseudocubic (pc) [010]-
75 oriented NdGaO₃ substrates (NGO). The heterostructures are defined as
76 NGO/CGO/[ESB/CGO]_N, where $N = 1, 3, 7, 10, 15$ is the number of [ESB/CGO] bilayers
77 schematically illustrated in Fig. 1a. The total thickness (d) of the thin films was fixed at
78 approximately 17 nm with a CGO to ESB thickness ratio of 1:1. The modulation length
79 (A) is the thickness of the [ESB/CGO] bilayers, which is related to d (the total thickness
80 of the film) and N (the number of repetitions) via $A = d/(N+1/2)$; for $N = 1, 3, 7, 10$ and
81 15, the values of A are 11.33, 4.86, 2.27, 1.62, and 1.10 nm, respectively. The high-angle
82 annular dark-field scanning transmission electron microscopy (HAADF-STEM) Z-

83 contrast images of NGO/CGO/[ESB/CGO]₇ reveal the epitaxial relationship between the
84 constituent layers, with ESB exhibiting a brighter ADF image contrast than CGO (Fig.
85 1b). The atomically resolved energy-dispersive X-ray (EDX) profiles of Ce, Er, and O
86 exhibit the compositional variation that enables the identification of well-defined
87 interfaces. Dopant segregation or formation of extended defects (e.g., dislocations or line
88 defects) is not observed down to $\lambda = 2.27$ nm; however, a further decrease in λ to 1.62
89 nm results in substantial chemical intermixing, as demonstrated by the electron energy
90 loss spectroscopy (EELS) and STEM-EDX results (Extended Data Fig. 1).

91 The electrostrictive response of the heterostructure is proportional to the square of the
92 electric field strength (Extended Data Fig. 2). The generated stress exceeds 9.7 GPa at the
93 maximum applied electric field of 17.4 kV/cm. Fig. 1c shows the electrostriction
94 coefficient (M_{xx}) of the heterostructure as a function of λ measured at 1 Hz. For ease of
95 comparison, the M_{xx} of a single layer of CGO thin film has been plotted along with the
96 reported coefficient values for CGO films of varying thickness ($d \geq 400$ nm).^{10, 12-14} For
97 single-layered films, λ is equal to the film thickness (d). A comparison with Bi₂O₃-based
98 films is not included as their electrostrictive properties have not yet been investigated
99 owing to their structural and chemical instabilities.^{11, 24, 25} As seen in Fig. 1c, the plot of
100 the measured M_{xx} exhibits a "volcano-like" shape as a function of $1/\lambda$, with the maximum
101 value measured at $\lambda = 2.27$ nm. The electrostriction coefficient increases linearly as $1/\lambda$
102 increases up to 0.44 nm^{-1} . This configuration corresponds to 7 bilayers of [ESB/CGO].

103 Further increases of $1/\lambda$ beyond 0.44 nm^{-1} lead to a decrease in the electrostriction
104 coefficient. The initial linearly increasing values align well with the reported M_{xx} values
105 for CGO, regardless of the deposition method, process parameters, film microstructure,
106 and type of substrate/electrode.^{10, 12-14} Remarkably, the maximum M_{xx} of the
107 heterostructure ($2.38 \times 10^{-14} \text{ m}^2/\text{V}^2$) is more than three orders of magnitude greater than
108 those of thick CGO films.^{10, 12-14} However, as λ decreases below $\lambda = 1.62 \text{ nm}$ ($N > 7$), the
109 electrostriction coefficient decreases substantially, which can be attributed to intermixing
110 at the interfaces (Extended Data Fig. 1) that results in deteriorated electrostriction.

111

112 The chemical stability and the electromechanical performance of heterostructures with
113 different stacking sequences were also investigated (Extended Data Fig. 3). When ESB
114 was deposited directly onto NGO (NGO/ESB/[CGO/ESB]₃), the heterostructure
115 exhibited a reduced electrostriction coefficient of $3.0 \times 10^{-16} \text{ m}^2/\text{V}^2$ (Extended Data Fig.
116 3). By contrast, when CGO was deposited onto NGO (NGO/CGO/[ESB/CGO]₃), the
117 heterostructure exhibited chemical stability with substantially enhanced electrostriction,
118 highlighting the importance of the stacking sequence. Therefore, we have used the
119 NGO/CGO/[ESB/CGO]_N as the main configuration for our experiments, where the
120 heterostructure is capped with CGO to prevent the degradation of the ESB layer. Fig. 1d
121 shows the plots of M_{xx} for heterostructures with $\lambda = 11.33, 2.27, \text{ and } 1.10 \text{ nm}$ as a function
122 of frequency. The performance of the heterostructures is superior to that of reported

123 individual electrostrictive materials, including bulk CGO,²⁶ Y/Nb:Bi₂O₃,¹¹ La₂Mo₂O₉,²⁷
124 Y:ZrO₂ (YSZ)¹¹, or commercial relaxor ferroelectrics, such as Pb(Mg_{1/3}Nb_{2/3})O₃-PbTiO₃
125 (PMN-PT),⁶ P(VDF-TrFE) copolymers⁹. The electrostriction of the heterostructures also
126 surpasses the recently discovered ultrahigh electrostriction of lead halide perovskites.²⁸
127 Similar to bulk CGO, the measured M_{xx} of the heterostructures decreases with an increase
128 in frequency ($1 \leq f \leq 200$ Hz): for $A = 2.27$ nm, it decreases from 2.38×10^{-14} m²/V² at 1
129 Hz to 3.76×10^{-15} m²/V² at 200 Hz. This enhanced electrostrictive response can be used
130 in novel applications. It reduces the operating electric field substantially, improving the
131 long-term stability of the devices and lowering their energy consumption.

132 A potential drawback of multilayers is the possible delamination at the interfaces after
133 cyclic electrical loading, which could lead to the failure of the electrostrictive devices.
134 Therefore, the fatigue behaviour of the NGO/CGO/[ESB/CGO]₇ heterostructure was
135 investigated as a function of time by applying a sinusoidal electric field with a constant
136 amplitude of 17.4 kV/cm at different frequencies (Extended Data Fig. 4). Notably, the
137 heterostructure remained electromechanically active, and the field-induced stress did not
138 degrade after 1000 cycles at 1 Hz. The electromechanical stability was further confirmed
139 by subsequent measurements at 50 and 200 Hz for another 1000 cycles (Extended Data
140 Fig. 4).

141 Fig. 2a shows the X-ray diffraction (XRD) reciprocal space mapping (RSM) analysis for
142 the heterostructures around the asymmetric (221)_{pc} reflection of NGO. The out-of-plane

143 position and shape of the (420) reflections of the heterostructures vary with a decrease in
144 λ . The overall structural coherency is maintained, indicating that the in-plane lattice
145 parameters of the heterostructure are coherent with respect to the substrate. This result is
146 consistent with the scanning transmission electron microscopy (STEM) results. The sub-
147 peaks along the out-of-plane direction observed for $\lambda = 11.33$ and 4.86 nm are attributed
148 to the lattice relaxations within the CGO and ESB layer. The XRD (2θ - ω scan) analysis
149 indicates that the heterostructures are phase-pure films oriented along the (110)
150 crystallographic direction (Fig. 2b). The Laue diffraction oscillations around the
151 superlattice peaks indicate that the periodicity of the fluorite lattice is well preserved for
152 different modulation lengths.

153 The fluorite oxides (CGO and ESB) grow epitaxially on the perovskite oxide (NGO) with
154 a rotation of 45° to account for the substantial mismatch and allow cube-on-cube growth.
155 This arrangement results in an epitaxial relationship of $\langle 110 \rangle_{\text{CGO}} // \langle 010 \rangle_{\text{pc NGO}}$ such that
156 the mismatch is reduced to $\sim 1\%$ (see Fig. 2c and Extended Data Fig. 1a).

157 The lattice mismatch between the heterostructure and the substrate is compensated
158 completely by the elastic strain, generating an average in-plane strain of 1% in the film
159 (see Fig. 2d and Supplementary Fig. 1). In contrast, the magnitude of the average out-of-
160 plane compressive strain decreases from ca. 1.5% to ca. 1% when λ is decreased from
161 11.33 to 2.27 (N increased from 1 to 7). Consequently, the volumetric strain ($\Delta V/V$)
162 increases from 0.48% to 0.99%, with $\lambda = 2.27$ nm being the largest. The abnormal change

163 in strain for $\lambda < 2.27$ nm is attributed to the chemical intermixing at the interfaces, as
164 shown in the EELS and EDX maps shown in Extended Data Fig. 1b and c. The variation
165 of out-of-plane strain (and hence $\Delta V/V$) as a function of λ correlates well with the
166 measured electrostriction coefficient (Fig. 1c).

167 Based on the structural analysis discussed above, we employed atomic-scale simulations
168 on heterostructures with alternating layers of CGO and ESB to investigate the structural
169 evolution as a function of λ . The simulations were performed by fixing the composition
170 to the experimental stoichiometry, i.e., $\text{Ce}_{0.8}\text{Gd}_{0.2}\text{O}_{1.9}$ and $\text{Er}_{0.4}\text{Bi}_{1.6}\text{O}_3$, respectively. The
171 model structures were optimised with the in-plane lattice parameters fixed to the NGO
172 substrate, while the out-of-plane lattice parameter was allowed to relax. The calculations
173 were performed for heterostructures with different modulation lengths, i.e., 96, 48, 32,
174 24, 16, 12, 8, 6, and 4 cationic planes, respectively. Fig. 3a shows a schematic illustration
175 of the modulation length, and the definition of the cationic interplanar distance (d_C)
176 projected in the out-of-plane direction. The amplitude of the lattice distortion at the
177 CGO/ESB interfaces was calculated based on the variation in d_C as a function of λ (Fig.
178 3b). For example, for $\lambda = 18.56$ nm (96 cationic planes), the lattice relaxation yields two
179 distinct plateaus at 1.92 and 1.96 Å, close to the individual interplanar distances of bulk
180 CGO and ESB, respectively. This range of values agrees well with the lattice relaxation
181 observed for $\lambda = 11.33$ and 4.86 nm ($N = 1$ and 3) in the RSMs shown in Fig. 2a.

182 The effect of the interfaces becomes progressively evident with a decrease in λ . The
183 interplanar distances become gradually frustrated with a reduction in λ down to 2.33 nm
184 and beyond (approaching $\lambda = 2.27$ nm for NGO/CGO[ESB/CGO]₇). At $\lambda = 0.78$ nm, it
185 is difficult to distinguish between the interfaces and individual regions, indicating that
186 CGO and ESB adopt similar lattice parameters.

187 We further evaluate the role of modulation length on electrostriction by two different
188 models: (1) A phenomenological model considering elastic and electric dipoles and (2)
189 molecular dynamics (MD) simulations. For the former case, we consider an ensemble of
190 elastic dipoles, where each is coupled to an electric dipole, as schematically illustrated in
191 the inset in Fig. 4a. The elastic-electric dipoles interact with an external electric field by
192 changing their orientation in space (Supplementary Information "Phenomenological
193 Simulation" section). M_{xx} is then calculated as a function of volumetric strain ($\Delta V/V$) to
194 mimic the strain state of the heterostructures as a result of the evolution of modulation
195 length. Fig. 4a shows that the calculated M_{xx} increases fast with the increase of $\Delta V/V$,
196 which is in agreement with the experimental observation of increasing lattice parameter
197 for increasing $1/\lambda$ up to 0.5 nm^{-1} (Fig. 3c), and the increase of M_{xx} in the same value range
198 of $1/\lambda$ (Fig. 1c).

199 We further employed MD simulations to investigate the effect of λ on electrostriction.
200 We apply an external electric field on the heterostructures, allowing the lattice parameters

201 ($a/b/c$) to relax (see Extended data Fig. 5). The results confirmed that the field-induced
202 strain exhibits a "volcano-like" shape as a function of λ (Fig. 4b).

203 To explore the applicability of multilayering for engineering electrostriction, we have
204 further investigated the field-induced strain as a function of λ with different defective
205 oxide structures (fluorite, perovskite, garnet, and spinel). These results are fully consistent
206 with the "volcano-like" behaviour, demonstrating that interfacial engineering is a
207 promising strategy to achieve large electrostriction (Extended data Fig. 6).

208 Here, we propose that the volumetric strain change in the heterostructure is associated
209 with substantial variation of the local distortions, leading to the coexistence of energy-
210 competing elastic dipoles (and hence electric dipoles). A radial distribution function
211 (RDF) analysis confirms this behaviour: decreasing λ , the radial distribution broadens,
212 indicating that the distances between the cations and the anions in the heterostructures
213 increase (see Extended data Fig. 7 and 8). We conclude that, in the strained multilayers
214 (without external electric field), the ions are not fixed to high-symmetry positions, gaining
215 thus in spatial freedom and thus increasing elastic and electrostatic energy
216 (Supplementary Information Fig. 2). When an electric field is applied, the electric dipoles,
217 which are coupled to elastic dipoles, are easier to polarise.^{29,30} They are then able to adjust
218 their relative positions, leading to larger M_{xx} . This effect becomes even more pronounced
219 when decreasing λ , owing to the increase in the strength of the elastic dipoles. However,
220 for λ beyond a certain value, the oxygen sublattice becomes disordered, and the

221 volumetric strain effect is lost (Fig. 3c), thus resulting in the decrease of electrostriction.
222 In short, the reduction in the modulation length λ plays a two-fold role: a) it increases the
223 strength of the elastic dipoles, and b) it leads to the coexistence of energy-competing
224 elastic dipoles, which are easier to switch between different directions in response to the
225 external electric field. Fig. 4c illustrates the mechanism schematically.

226 In conclusion, we show that the electrostriction effect can be designed and manipulated
227 by artificial heterostructures. This framework provides new insights into the role of
228 interfacial strain discontinuities, which can be further extended to other defective oxide
229 systems. Such strain modulation results in the displacement of ions away from the ideal
230 lattice sites. It provides the degree of freedom required to control the strength of the elastic
231 dipoles and their ability to reorient, which is a key reason for achieving a large
232 electrostriction coefficient in ultrathin heterostructures. These factors are a prerequisite
233 for replacing lead-based piezoelectric materials (such as commercial PMN-PT) with
234 environment-friendly and non-toxic electrostrictors with superior, reliable, and optimised
235 properties, making them suitable for a wide range of applications, including optical
236 communication, biomedical actuation, and micro-sensors.

237

238 **Online content**

239 Any methods, additional references, Nature Research reporting summaries, source data,
240 extended data, supplementary information, acknowledgements, peer review information,

241 details of author contributions and competing interests, and statements of data and code
242 availability are available at <http://npg.nature.com>.
243
244 1. Ramesh, R. & Schlom, D. G. Creating emergent phenomena in oxide superlattices. *Nat. Rev. Mater.* **4**,
245 257-268 (2019).
246 2. Yang, M. M. et al. Piezoelectric and pyroelectric effects induced by the interface polar symmetry. *Nature*
247 **584**, 377-381 (2020).
248 3. Li, F., Jin, L., Xu, Z., Zhang, S. Electrostrictive effect in ferroelectrics: An alternative approach to
249 improve piezoelectricity. *Appl. Phys. Rev.* **1**, 011103 (2014).
250 4. Lehmann, W. et al. Giant lateral electrostriction in ferroelectric liquid-crystalline elastomers. *Nature* **410**,
251 447-450 (2001).
252 5. Yimnirun, R., Moses, P. J., Newnham, R. E. & Meyer Jr, R. J. Electrostrictive strain in low-permittivity
253 dielectrics. *J. Electroceram.* **8**, 87-98 (2002).
254 6. Li, F., Jin, L., Xu, Z., Wang, D. & Zhang, S. Electrostrictive effect in $\text{Pb}(\text{Mg}_{1/3}\text{Nb}_{2/3})\text{O}_3\text{-xPbTiO}_3$ crystals.
255 *Appl. Phys. Lett.* **102**, 152910 (2013).
256 7. Zednik, R. J., Varatharajan, A., Oliver, M., Valanoor, N. & McIntyre, P. C. Mobile ferroelastic domain
257 walls in nanocrystalline PZT films: The direct piezoelectric effect. *Adv. Funct. Mater.* **21**, 3104-3110
258 (2011).
259 8. Li, F. et al. Ultra-high piezoelectricity in ferroelectric ceramics by design. *Nat. Mater.* **17**, 349-354
260 (2018).

- 261 9. Zhang, Q. M., Bharti, V. & Zhao, X. Giant electrostriction and relaxor ferroelectric behaviour in electron-
262 irradiated poly(vinylidene fluoride-trifluoroethylene) copolymer. *Science* **280**, 2101-2104 (1998).
- 263 10. Korobko, R. et al. Giant electrostriction in Gd-doped ceria. *Adv. Mater.* **24**, 5857-5861 (2012).
- 264 11. Yavo, N. et al. Large nonclassical electrostriction in (Y, Nb)-stabilised δ -Bi₂O₃. *Adv. Funct. Mater.* **26**,
265 1138-1142 (2016).
- 266 12. Korobko, R. et al. In situ extended X-ray absorption fine structure study of electrostriction in Gd-doped
267 ceria. *Appl. Phys. Lett.* **106**, 042904 (2015).
- 268 13. Hadad, M., Ashraf, H., Mohanty, G., Sandu, C. & Murali, P. Key-features in processing and
269 microstructure for achieving giant electrostriction in gadolinium-doped ceria thin films. *Acta Mater.* **118**,
270 1-7 (2016).
- 271 14. Santucci, S., Zhang, H., Sanna, S., Pryds, N. & Esposito, V. Enhanced electromechanical coupling of
272 TiN/Ce_{0.8}Gd_{0.2}O_{1.9} thin film electrostrictor. *APL Mater.* **7**, 071104 (2019).
- 273 15. Sata, N., Eberman, K., Eberl, K., & Maier, J. Mesoscopic fast ion conduction in nanometer-scale planar
274 heterostructures. *Nature* **408**, 946-949 (2000).
- 275 16. Domínguez, C. et al. Length scales of interfacial coupling between metal and insulator phases in oxides.
276 *Nat. Mater.* **19**, 1182-1187 (2020).
- 277 17. Haeni, J. H. et al. Room-temperature ferroelectricity in strained SrTiO₃. *Nature* **430**, 758-761 (2004).
- 278 18. Cancellieri, C. et al. Electrostriction at LaAlO₃/SrTiO₃ interface. *Phys. Rev. Lett.* **107**, 056102 (2011).
- 279 19. Junquera, J. & Ghosez, P. Critical thickness for ferroelectricity in perovskite ultrathin films. *Nature*
280 **422**, 506-509 (2003).

- 281 20. Fong, D. D. et al. Ferroelectricity in ultrathin perovskite films. *Science* **304**, 1650-1653 (2004).
- 282 21. Mani, B. K., Chang, C. M., Lisenkov, S. & Ponomareva, I. Critical Thickness for Antiferroelectricity
283 in PbZrO₃. *Phys. Rev. Lett.* **115**, 097601 (2015).
- 284 22. Zhang, W. & Ouyang, J. Interface engineering of ferroelectric thin heterostructures. Nanostructures in
285 ferroelectric films for energy applications include domains, grains, interfaces, and engineering methods
286 (Elsevier Inc., 2019). doi:[10.1016/B978-0-12-813856-4.00006-5](https://doi.org/10.1016/B978-0-12-813856-4.00006-5).
- 287 23. Ji, D. et al. Freestanding crystalline oxide perovskites down to monolayer limit *Nature* **570**, 87-90
288 (2019).
- 289 24. Sanna, S. et al. Enhancement of chemical stability in confined δ -Bi₂O₃. *Nat. Mater.* **14**, 500-504 (2015).
- 290 25. Sanna, S. et al. Structural instability and electrical properties of epitaxial Er₂O₃-stabilized Bi₂O₃ thin
291 films. *Solid State Ionics.* **266**, 13-18 (2014).
- 292 26. Varenik, M. et al. Dopant concentration controls the quasi-static electrostrictive strain response of ceria
293 ceramics. *ACS Appl. Mater. Interfaces.* **12**, 39381-39387 (2020).
- 294 27. Li, Q. et al. Giant thermally enhanced electrostriction and polar surface phases in La₂Mo₂O₉ oxygen
295 ion conductors. *Phys. Rev. Materials.* **2**, 041403(R) (2018).
- 296 28. Chen, B. et al. Large electrostrictive responses in lead halide perovskites. *Nat. Mater.* **17**, 1020-1026
297 (2018).
- 298 29. Das, T. et al. Anisotropic chemical strain in cubic ceria due to oxygen-vacancy-induced elastic dipoles.
299 *Phys. Chem. Chem. Phys.* **20**, 15293-15299 (2018).

300 30. Kraynis, O. et al. Modeling Strain Distribution at the Atomic Level in Doped Ceria Films with Extended
301 X-ray Absorption Fine Structure Spectroscopy. *Inorg. Chem.* **58**, 7527-7536 (2019).

302

303 **Acknowledgements**

304 This research was supported by the BioWings project funded by the European Union's
305 Horizon 2020, Future and Emerging Technologies (FET) programme (Grant No. 801267)
306 and the Danish Council for Independent Research Technology and Production Sciences
307 for the DFF- Research Project 2 (Grant No. 48293). N.P. and D.V.C. acknowledge
308 funding from Villum Fonden for the NEED project (00027993) and the Danish Council
309 for Independent Research Technology and Production Sciences for the DFF- Research
310 Project 3 (Grant No 00069 B). V.E. acknowledges funding from Villum Fonden for the
311 IRIDE project (00022862). N.G. and J.V. acknowledge funding from the GOA project
312 ("Solarpaint") of the University of Antwerp. The microscope used in this work was partly
313 funded by the Hercules Fund from the Flemish Government. D.J. acknowledges funding
314 from the FWO Project G093417N from the Flemish Fund for Scientific Research. D.C.
315 acknowledges the TOP/BOF funding of the University of Antwerp. This project has
316 received funding from the European Union's Horizon 2020 Research Infrastructure -
317 Integrating Activities for Advanced Communities under grant agreement No 823717-
318 ESTEEM3. The authors would like to thank Thierry Désiré Pomar and Achilles John
319 Bergne for English proofreading.

320

321 **Author Contributions**

322

323 H. Z., N. P., and V. E. conceived the idea and designed the project. H.Z. and S.S. prepared
324 the samples and characterised their electromechanical properties. N.G. performed STEM
325 measurements and analysed the STEM-EELS results. D.J. assisted with the processing of
326 the HAADF-STEM data analysis, and D.C. performed the statistical analysis of the EDX
327 results under the supervision of N.G. and J.V. D.P., P.M., D. D. and R.D. performed the
328 XRD and RSM characterisation. H. Z., I. L. and I. E. C. performed atomic-scale
329 simulations and analysis. D. V. C. performed finite element simulations. A. R. I., I. L.
330 and P. M. developed the analytical model. H.Z., V.E. and N.P. wrote the manuscript with
331 input from all the authors. All authors have read and agreed to the published version of
332 the manuscript.

333 **Competing interests** The authors declare no competing financial interests.

334

335 **Additional information**

336

337 **Supplementary information** is available for this paper at www.nature.com.

338 **Correspondence and requests for materials** should be addressed to H. Z., V. E., and N. P.

339 **Reprints and permissions** information is available online at <http://npg.nature.com/reprintsandpermissions>.

340

341 **Methods**

342 **Thin-film fabrication.** The heterostructures were fabricated by alternating CGO and
343 ESB layers using PLD with a multi-target carousel. The target–substrate distance was 50
344 mm. The 248 nm KrF excimer laser was operated at 2 Hz with a laser fluence of 1.8 J
345 cm⁻². The deposition rate was ~0.05 Å per pulse. The total number of laser shots on the
346 targets were 3560 (1780 for CGO and 1780 for ESB), yielding a total thickness of ~17

347 nm. The ratio of CGO to ESB was fixed at 1:1, whereas the thickness of each layer varied
348 with the modulation length. The deposition was performed at 600 °C at an oxygen partial
349 pressure of 10^{-3} mbar. The heating/cooling rate was 10 °C/min. The Au top electrodes
350 were sputtered with a Bal-Tec SCD 005 sputter coater at room temperature.

351 **STEM, EDX, and EELS measurements** The cross-sectional transmission electron
352 microscopy (TEM) lamellae were prepared via focused ion beam using an FEI HELIOS
353 650 dual-beam focused ion beam device. Carbon and platinum protective layers were
354 deposited on the top of the film during the preparation process. The aberration-corrected
355 HAADF-STEM and EDX were performed using a probe aberration-corrected 'cubed' FEI
356 TITAN 80-300 electron microscope operated at 300 kV equipped with SUPER-X EDX
357 detector system. Line profiles of the elemental distribution along the TEM lamellae were
358 averaged over several unit cells laterally for better statistical analysis. The EELS data
359 were acquired on a double aberration-corrected 'cubed' FEI-TITAN 80-300 electron
360 microscope operated at 120 kV in monochromatic mode, providing an energy resolution
361 of 150 meV.

362 **XRD and RSMs analysis.** The crystal structure and strain states were characterised using
363 a high-resolution Bruker D8 discover diffractometer with monochromatic Cu $K_{\alpha 1}$
364 radiation ($\lambda = 1.5406$ Å). Reciprocal space mapping was performed around the (221)
365 asymmetric reflection of the NGO substrate.

366 **Electrostriction measurements** The electrostriction properties of the heterostructures
367 were measured using a planar electrode configuration, with the two electrodes placed on
368 top of the thin films in parallel (inset in Fig. 1c). The sinusoidal electric field was
369 generated using an AIM-TTI TGP 3100 function generator, amplified by a Trek 2220

370 amplifier. The deflection at the free end of the cantilever was measured using a single-
 371 beam laser interferometer SIOS NA analyser at the second harmonic of the electrical
 372 field. An Ametek 7230 DSP lock-in amplifier was used to improve the signal-to-noise
 373 ratio (down to 0.2 nm). Additional details can be found in Supplementary Fig. 3. The
 374 electric field distribution within the cantilever was modelled using the finite element
 375 simulations, as shown in Supplementary Fig. 4.

376 **Atomic-scale Simulations** Atomic-scale simulations were performed based on the Born
 377 model of ionic solids.³¹ This approach has been used extensively to model the effect of
 378 an electric field for various material systems, such as polarisation-electric field hysteresis
 379 and electro-strain hysteresis of ferroelectrics,³² caloric effects of MAPbI₃,³³ and mobility
 380 of oxygen ions in CeO₂.³⁴ The ions are treated as classical particles, whereas the
 381 interatomic interactions are described by

$$382 \quad V_{ij} = \frac{Z_i Z_j}{4\pi\epsilon_0 r_{ij}} + A_{ij} \exp\left(-\frac{r_{ij}}{\rho_{ij}}\right) - \frac{C_{ij}}{r_{ij}^6} \quad 1$$

383 where the first term describes the long-range Coulomb interactions and the following two
 384 terms correspond to the short-range electron cloud overlap and dispersion, respectively.
 385 The parameters r_{ij} , $Z_{i(j)}$, and ϵ_0 correspond to the distance between ions i and j , the
 386 valences of the ions, and the permittivity of free space, respectively;

387 During the simulation of the structural evolution as a function of λ (Fig. 3 and
 388 Extended data Figure 7), the in-plane lattice parameters were kept fixed, whereas the out-
 389 of-plane lattice parameters were free to relax. For the calculation of the electrostriction

390 coefficient, the in-plane and out-of-plane lattice parameters were free to relax in response
391 to the electric field (Fig. 4b and Extended data Figs. 5 and 6). Extended Data Fig. 8 shows
392 a schematic illustration of the elastic dipoles resulting from local lattice distortions.
393 During the simulations, the temperature was monitored using a Nosé–Hoover
394 thermostat,^{35, 36} as implemented in the LAMMPS package.³⁷ More details about the
395 empirical Buckingham parameters and the supercell configurations can be found in
396 Supplementary Fig. 4 and the related text.

397 **Phenomenological simulations** This model considered an ensemble of elastic dipoles,
398 each elastic rigidly connected to an electric dipole. The elastic-electric dipoles were
399 assumed to interact with an initial strain field and external electric field by changing their
400 orientation in space. The equilibrium orientation was obtained by minimizing the sum of
401 the total energy (E_{total}) of the system:

$$402 \quad E_{\text{total}} = E_{\text{elastic}} + E_{\text{electric}} \quad 2$$

403 where E_{elastic} and E_{electric} are the elastic and electric contributions, respectively. The
404 effect of modulation length was captured by calculating the electrostriction coefficient as
405 a function of the volumetric strain ($\Delta V/V$), which varied as a result of the modulation
406 length change. More details about the interactions between the elastic and electric dipoles
407 and their response to the external field can be found in Supplementary Fig. 5 and the
408 related text.

409

410 **Data Availability**

411 The data supporting this study's findings are available from the corresponding authors
412 upon reasonable request.

413 **Code Availability**

414 The code used for the creation of physical model and atomic-scale models are available
415 from the corresponding authors upon reasonable request.

416

417 31. Born, M. and Mayer, J. E. Zur gittertheorie der ionenkristalle, *Z. Phys.* **75**, 1 (1932).

418 32. Chapman, J. B. J., Cohen, R. E., Kimmel, A. V. and Duffy, M. D. Improving the functional control of
419 aged ferroelectrics using insights from atomistic modeling, *Phys. Rev. Lett.* **119**, 177602 (2017).

420 33. Liu, S. and Cohen, R. E. Response of methylammonium lead iodide to external stimuli and caloric
421 effects from molecular dynamics simulations, *J. Phys. Chem. C.* **120**, 17274-17281 (2016).

422 34. Genreith-Schriever, A. and De Souza, R. A. Field-enhanced ion transport in solids: Reexamination with
423 molecular dynamics simulations, *Phys. Rev. B.* **94**, 224304 (2016);

424 35. Nosé, S. A unified formulation of the constant temperature molecular dynamics methods. *J. Chem.*
425 *Phys.* **81**, 511-519 (1984).

426 36. William G. Hoover. Canonical dynamics: Equilibrium phase-space distributions William. *Phys. Rev. A.*
427 **31**, 1695-1697 (1985).

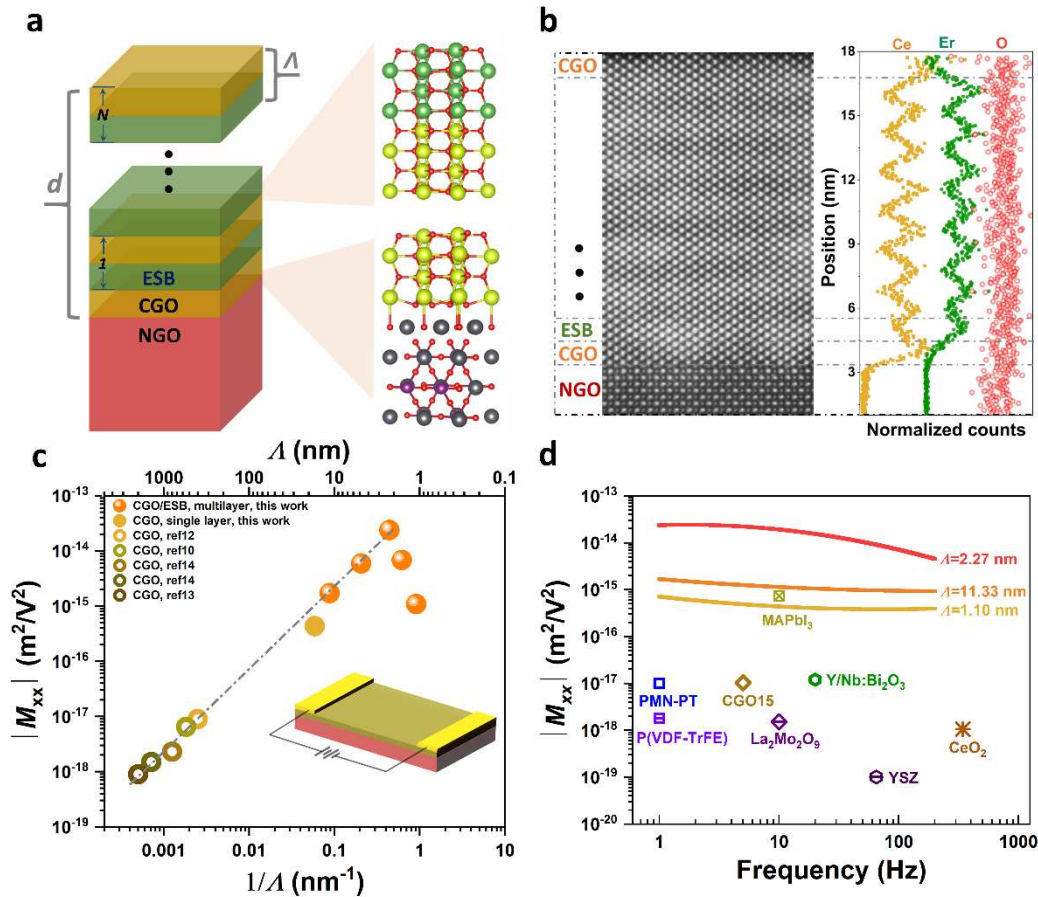
428 37. Plimpton, S. Fast Parallel Algorithms for Short-Range Molecular Dynamics. *J. Comput. Phys.* **117**, 1-
429 19 (1995).

430

431 **Figure legends:**

432

433 **Figure 1**



434

435 **Fig. 1 | Multilayer structure and electrostrictive property of NGO/CGO/[ESB/CGO]_N.** a, Schematic illustration of

436 the multilayer architecture. b, HAADF-STEM image and EDX compositional variations for $\lambda = 2.27$ nm. c,

437 Electrostriction coefficient (M_{xx}) as a function of modulation length (λ) measured at 1 Hz. The inset schematically

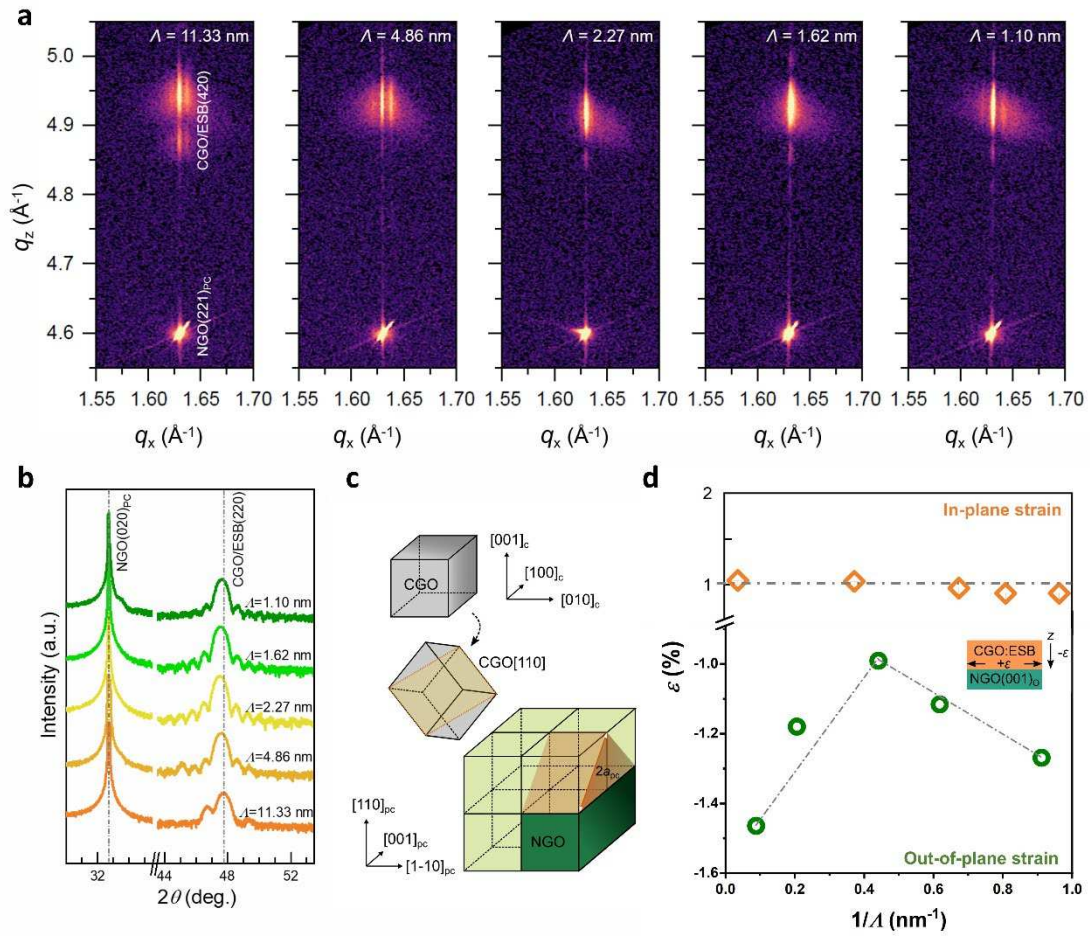
438 illustrates the top-top electrode configuration. d, Electrostriction coefficient (M_{xx}) as a function of frequency for

439 heterostructures with $\lambda = 11.33, 2.27,$ and 1.10 nm. Electrostriction properties of various electrostrictive materials are

440 shown for comparison: CeO₂,²⁶ CGO15,²⁶ Y/Nb:Bi₂O₃,¹¹ YSZ,¹¹ La₂Mo₂O₉,²⁷ PMN-PT,⁶ P(VDF-TrFE),⁹ and

441 MAPbI₃.²⁸

442 **Figure 2**

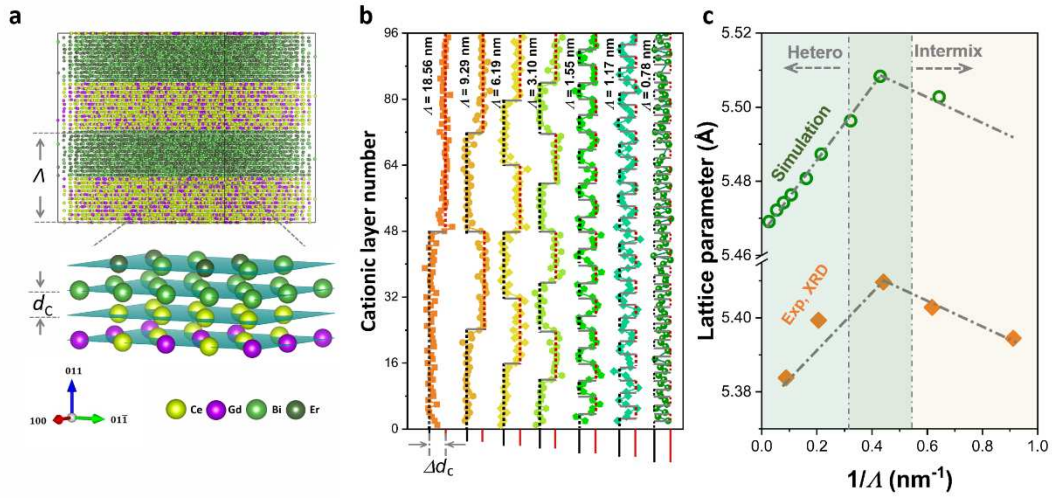


443

444 **Fig. 2| Structural analysis of NGO/CGO/[ESB/CGO]_N.** **a**, Reciprocal space mappings (RSMs) of the
 445 NGO/CGO/[ESB/CGO]_N heterostructures around the asymmetric (221)_{pc} reflection of the NGO substrate. **b**, X-ray
 446 diffraction pattern (2θ - ω scans) of the films. **c**, Schematic illustration of the epitaxial relationship between the
 447 heterostructure and the NGO substrate. **d**, Evolution of the in-plane and out-of-plane strains. The in-plane and out-of-
 448 plane strains are calculated based on the RSMs and 2θ - ω scans, respectively. The error bars in **d** represent the fitting
 449 error of the lattice constants.

450

451 **Figure 3**



452

453 **Fig. 3 | Mechanism of interlayer interaction.** **a**, Schematic illustration of the modulation length (Λ) and the cationic

454 interplanar distance (d_c) for the heterostructures. The oxygen ions are omitted for clarity. **b**, Variation of d_c as a function

455 of Λ projected onto the out-of-plane direction. The dark and red dot lines represent the individual interplanar distances

456 of CGO (1.92 Å) and ESB (1.96 Å), respectively. Δd_c is 0.04 Å. **c**, Variation of the out-of-plane lattice parameters as

457 a function of $1/\Lambda$. The dash-dotted lines are included as a guide to the eye only.

458

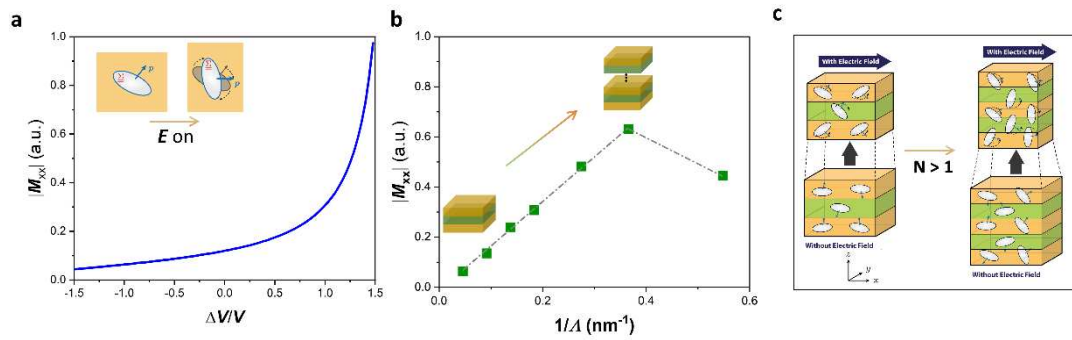
459

460

461

462

463



464

465 **Figure 4**

466 **Fig. 4| Mechanism of the enhanced electrostriction. a**, Electrostriction coefficient as a function of volumetric strain.

467 The inset is a schematic illustration of the coupling between the electric dipole and elastic dipole, where $\bar{\Sigma}$, p , ϵ , and E

468 denote elastic dipole, electric dipole, strain field and electric field, respectively. **b**, Electrostriction coefficient as a

469 function of modulation length. **c**, Schematical illustration of the mechanism showing the distribution and reorientation

470 of elastic dipoles within heterostructures with different modulation lengths with and without external electric field.

471

472

473

474

475

476

477

478

479 **Extended Data Figure legends:**

480 **Extended Data Figure 1 | STEM analysis of the heterostructures.** **a.** HAADF-STEM images for
481 NGO/CGO[ESB/CGO]₁₀ viewed along the [110] and [001] directions of the substrate from left to right, respectively.
482 **b.** STEM-EELS compositional maps. For each sample, the leftmost image is the HAADF signal acquired
483 simultaneously with the EELS measurement, followed by cerium $M_{4,5}$ in red, erbium $M_{4,5}$ in yellow, and neodymium
484 $M_{4,5}$ in green (colour code: Ce: red; Er: yellow, Nd: green). **c.** STEM-EDX compositional maps.

485 **Extended Data Figure 2 | Electrostriction Measurements** **a.** Electrostrictive response of NGO/CGO/[ESB/CGO]₇
486 under an alternating electric field. The strain developed at the second harmonic of the applied electric field. **b.** Field-
487 induced stress as a function of the electrical field for NGO/CGO/[ESB/CGO]_N measured at 1 Hz. The field-induced
488 stress increases linearly with an increase in the squared electric field. No saturation was observed within the measured
489 electric field range, regardless of the modulation length. The dash-dotted lines represent linear fittings of the measured
490 results.

491 **Extended Data Figure 3 | Electrostriction measurements for heterostructures with different stacking sequences.**
492 Comparison of electrostriction coefficients for thick CGO films and bulk materials Multilayer* denotes
493 NGO(100)/ESB/CGO/.../CGO, where ESB was deposited as the first layer.

494 **Extended Data Figure 4 | Fatigue measurements.** Electromechanical response of NGO/CGO/[ESB/CGO]₇ as a
495 function of time. **a.** Electric field. **b.** Electromechanical stress in response to an electric field at 1 Hz **c.**
496 Electromechanical stress as a function of the measured cycles at 1, 50, and 200 Hz. All measurements were performed
497 by applying a sinusoidal electric field with a constant amplitude of 17.4 kV/cm.

498 **Extended Data Figure 5 | Calculated field-induced strains in different directions.** a. CGO20; b. ESB20; c.
 499 heterostructure ($\lambda = 2.33$ nm). An electrical field was applied along the (100)-crystallographic direction. All lattice
 500 parameters were allowed to relax during the application of the electrical field. ϵ_{xx} , ϵ_{xy} , and ϵ_{xz} denote the strain developed
 501 along the X -, Y -, and Z -axis, respectively when the electric field is applied along with the X -axis. The Cartesian axes X ,
 502 Y , and Z correspond to the (100), (01-1) and (011) crystallographic directions, respectively. Note that the lattices of
 503 CGO20, ESB20, and the heterostructure exhibit similar deformation in response to an electric field, that is, contract
 504 along the (100)-crystallographic direction and expand along with the (011) and (01-1)-crystallographic directions.

505 **Extended Data Figure 6 | Electrostriction as a function modulation length for heterostructures with different**
 506 **crystal structures.** a. fluorite: CGO20/YSZ8; b. perovskite: SFTO10/BYZO10; c. garnet: GGMO10/LSFO10; d.
 507 spinel: MGMO10/ZAZO10. The chemical formula for YSZ8, SFTO10, BYZO10, GGMO10, LSFO10, MGMO10 and
 508 ZAZO10 are $(\text{Zr}_{0.92}^{4+}\text{Y}_{0.08}^{3+})\text{O}_{1.96}^{2-}$, $\text{Sr}_{1.0}^{2+}(\text{Fe}_{0.1}^{3+}\text{Ti}_{0.9}^{4+})\text{O}_{2.95}^{2-}$, $\text{Ba}_{1.0}^{2+}(\text{Y}_{0.1}^{3+}\text{Zr}_{0.9}^{4+})\text{O}_{2.95}^{2-}$, $\text{Gd}_{3.0}^{3+}(\text{Ga}_{4.5}^{3+}\text{Mg}_{0.5}^{2+})\text{O}_{11.75}^{2-}$,
 509 $(\text{La}_{2.5}^{3+}\text{Sr}_{0.5}^{2+})\text{Fe}_{5.0}^{3+}\text{O}_{11.75}^{2-}$, $\text{Mg}_{1.0}^{2+}(\text{Ga}_{1.8}^{3+}\text{Mg}_{0.2}^{2+})\text{O}_{3.90}^{2-}$, $\text{Zn}_{1.0}^{2+}(\text{Al}_{1.8}^{3+}\text{Zn}_{0.2}^{2+})\text{O}_{3.90}^{2-}$, respectively. The defects are generated at
 510 random within the heterostructures. The insets schematically show the unit cell of the ideal structure. All the lattice
 511 parameters are allowed to relax during the application of the electrical field. Note that the optimal modulation length
 512 yielding maximized electrostriction coefficient (M_{xx}) is material dependent.

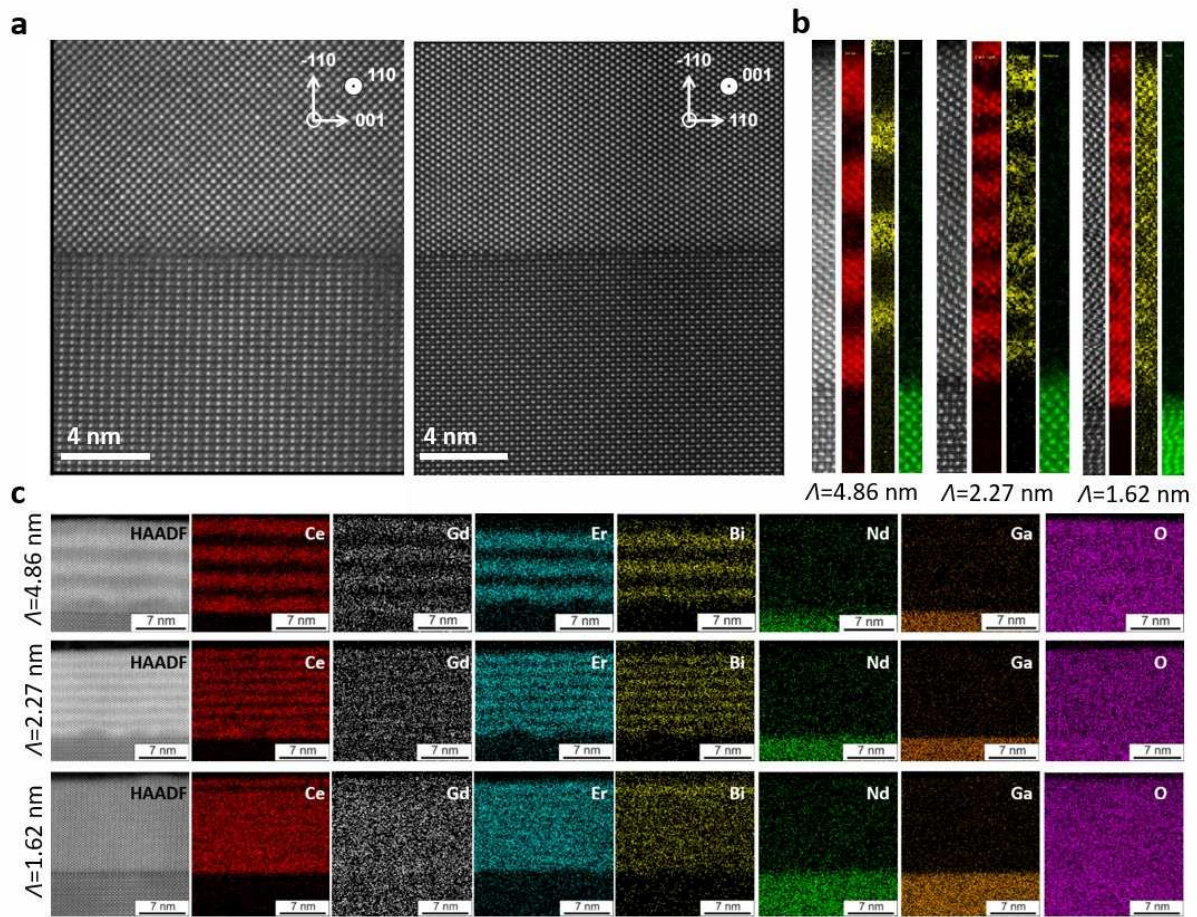
513 **Extended Data Figure 7 | Ion distribution within the heterostructures.** Radial distribution function of
 514 heterostructures as a function of modulation length (λ). The first, second, and third peaks correspond to the cation–
 515 anion, anion–anion, and cation–cation distances, respectively. No electric field was applied.

516 **Extended Data Figure 8 | Mechanism of elastic dipole and electric dipole formation.** a. An ideal tetrahedron with
 517 cations having equivalent distances and three C_2 symmetry axes present. Schematic illustration of the elastic dipole

518 formation resulting from tetrahedral deformation along the **b.** (100), **c.** (010), and **d.** (001) directions. The off-site
519 displacements of the cations result in local-symmetry breaking. Note that replacing one of the ions with Gd will result
520 in a structure with three variants that are equivalent to the distortion of Ceria without Gd.

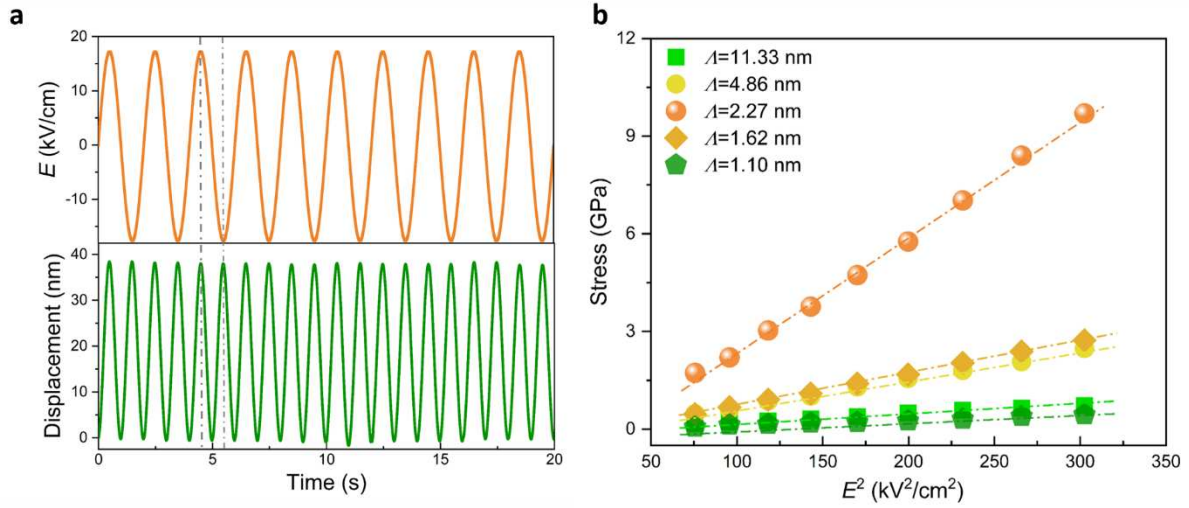
521

522



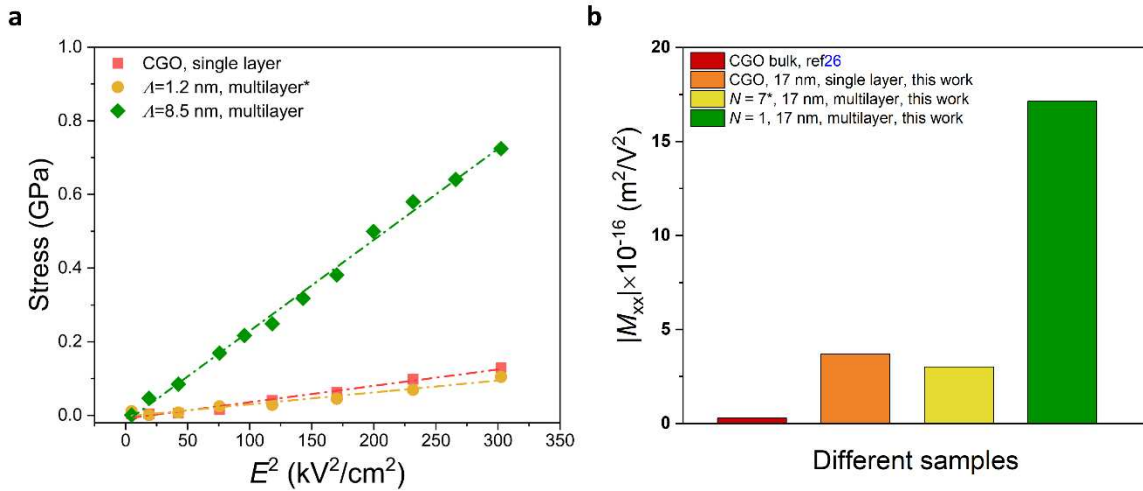
Extended Data Figure 1 | STEM analysis of the heterostructures.
a. HAADF-STEM images for NGO/CGO[ESB/CGO]₁₀ viewed along the [110] and [001] directions of the substrate from left to right, respectively.
b. STEM-EELS compositional maps. For each sample, the leftmost

image is the HAADF signal acquired simultaneously with the EELS measurement, followed by cerium $M_{4,5}$ in red, erbium $M_{4,5}$ in yellow, and neodymium $M_{4,5}$ in green (colour code: Ce: red; Er: yellow, Nd: green). **c.** STEM-EDX compositional maps.



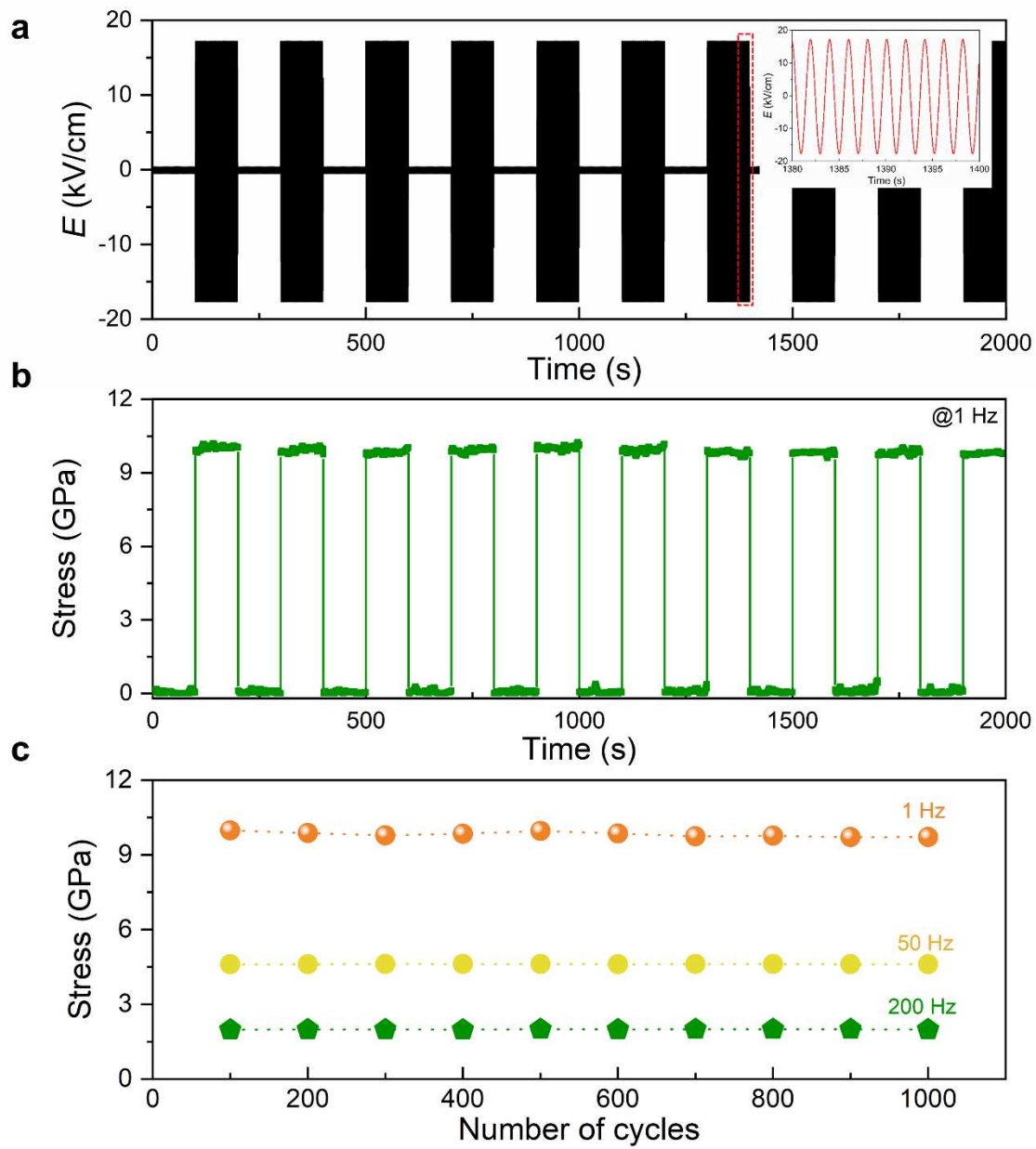
Extended Data Figure 2 | Electrostriction Measurements a. Electrostrictive response of NGO/CGO/[ESB/CGO]₇ under an alternating electric field. The strain developed at the second harmonic of the applied electric field. **b.** Field-induced stress as a function of the electrical field for NGO/CGO/[ESB/CGO]_N measured at 1 Hz. The field-

induced stress increases linearly with an increase in the squared electric field. No saturation was observed within the measured electric field range, regardless of the modulation length. The dash-dotted lines represent linear fittings of the measured results.



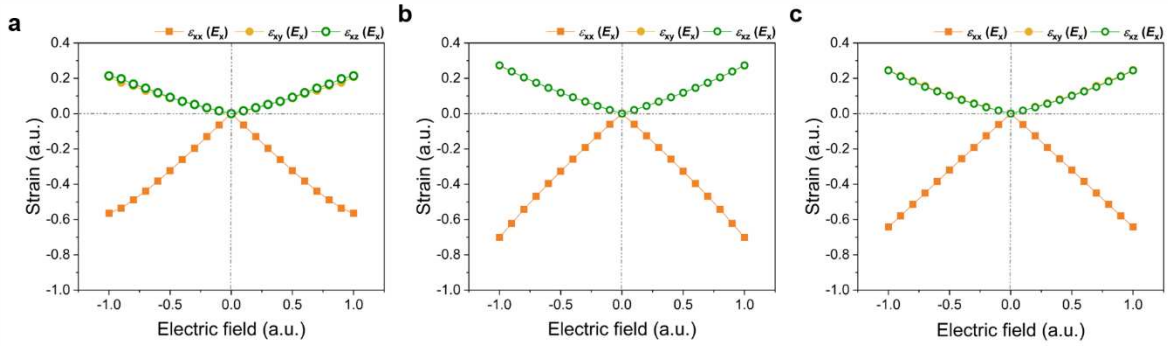
Extended Data Figure 3 | Electrostriction measurements for heterostructures with different stacking sequences. Comparison of electrostriction coefficients for thick CGO films and bulk materials

Multilayer* denotes NGO(100)/ESB/CGO/.../CGO, where ESB is deposited as the first layer.



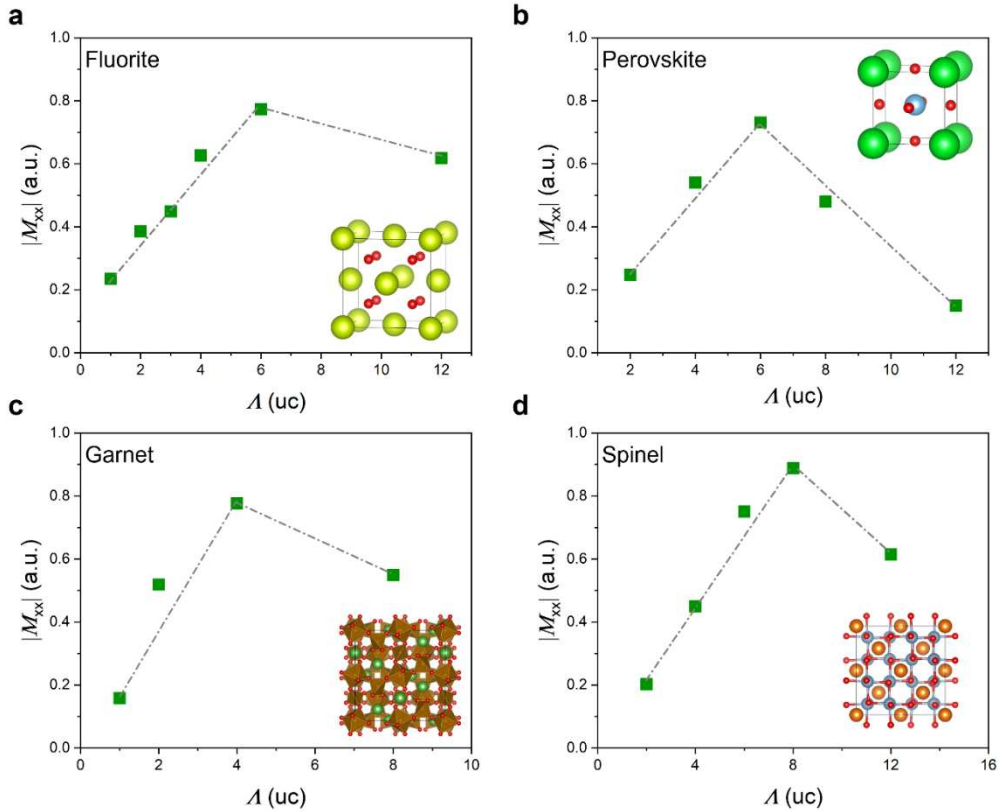
Extended Data Figure 4 | Fatigue measurements. Electromechanical response of NGO/CGO/[ESB/CGO]₇ as a function of time. **a.** Electric field. **b.** Electromechanical stress in response to an electric field at 1 Hz **c.** Electromechanical stress as a function of the

measured cycles at 1, 50, and 200 Hz. All measurements were performed by applying a sinusoidal electric field with a constant amplitude of 17.4 kV/cm.



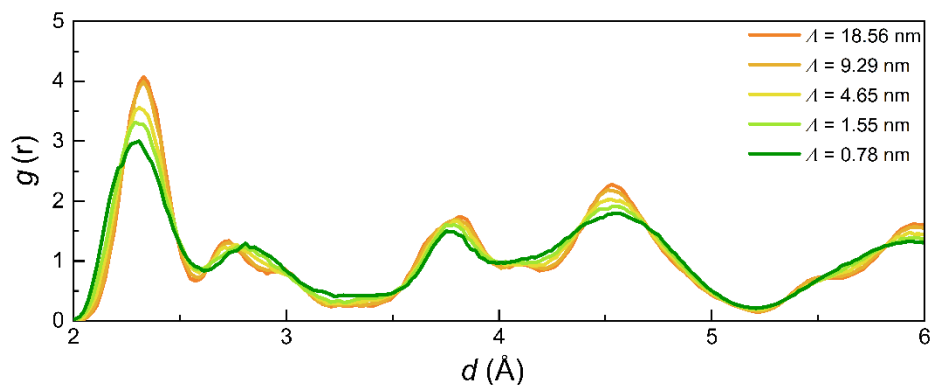
Extended Data Figure 5 | Calculated field-induced strains in different directions. a. CGO20; b. ESB20; c. heterostructure ($\lambda = 2.33$ nm). An electrical field was applied along the (100)-crystallographic direction. All lattice parameters were allowed to relax during the application of the electrical field. ϵ_{xx} , ϵ_{yy} , and ϵ_{zz} denote the strain developed along the X-, Y-, and Z-axis, respectively when the

electric field is applied along with the X-axis. The Cartesian axes X, Y, and Z correspond to the (100), (01-1) and (011) crystallographic directions, respectively. Note that the lattices of CGO20, ESB20, and the heterostructure exhibit similar deformation in response to an electric field, that is, contract along the (100)-crystallographic direction and expand along with the (011) and (01-1)-crystallographic directions.



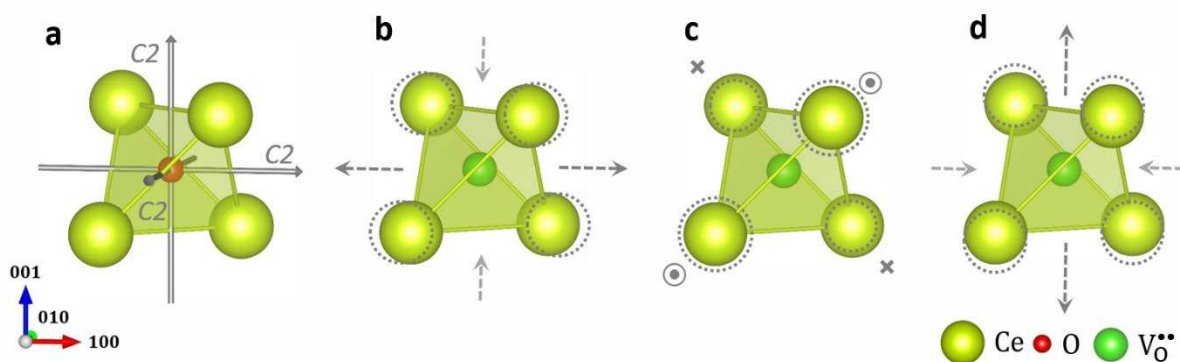
Extended Data Figure 6 | Electrostriction as a function of modulation length for heterostructures with different crystal structures. a. fluorite: CGO20/YSZ8; b. perovskite: SFTO10/BYZO10; c. garnet: GGMO10/LSFO10; d. spinel: MGMO10/ZAZO10. The chemical formula for YSZ8, SFTO10, BYZO10, GGMO10, LSFO10, MGMO10 and ZAZO10 are $(\text{Zr}_{0.92}^{4+}\text{Y}_{0.08}^{3+})\text{O}_{1.96}^{2-}$, $\text{Sr}_{1.0}^{2+}(\text{Fe}_{0.1}^{3+}\text{Ti}_{0.9}^{4+})\text{O}_{2.95}^{2-}$, $\text{Ba}_{1.0}^{2+}(\text{V}_{0.1}^{3+}\text{Zr}_{0.9}^{4+})\text{O}_{2.95}^{2-}$, $\text{Gd}_{3.0}^{3+}(\text{Ga}_{4.5}^{3+}\text{Mg}_{0.5}^{2+})\text{O}_{11.75}^{2-}$, $(\text{La}_{2.5}^{3+}\text{Sr}_{0.5}^{2+})\text{Fe}_{5.0}^{3+}\text{O}_{11.75}^{2-}$,

$\text{Mg}_{1.0}^{2+}(\text{Ga}_{1.8}^{3+}\text{Mg}_{0.2}^{2+})\text{O}_{3.90}^{2-}$, $\text{Zn}_{1.0}^{2+}(\text{Al}_{1.8}^{3+}\text{Zn}_{0.2}^{2+})\text{O}_{3.90}^{2-}$, respectively. The defects are generated at random within the heterostructures. The insets schematically show the unit cell of the ideal structure. All the lattice parameters are allowed to relax during the application of the electrical field. Note that the optimal modulation length yielding maximized electrostriction coefficient (M_{xx}) is material dependent.



Extended Data Figure 7 | Ion distribution within the heterostructures. Radial distribution function of heterostructures as a function of modulation length (λ). The first, second, and third peaks

correspond to the cation–anion, anion–anion, and cation–cation distances, respectively. No electric field was applied.



Extended Data Figure 8 | Mechanism of elastic dipole and electric dipole formation. a. An ideal tetrahedron with cations having equivalent distances and three C_2 symmetry axes present. Schematic illustration of the elastic dipole formation resulting from tetrahedral

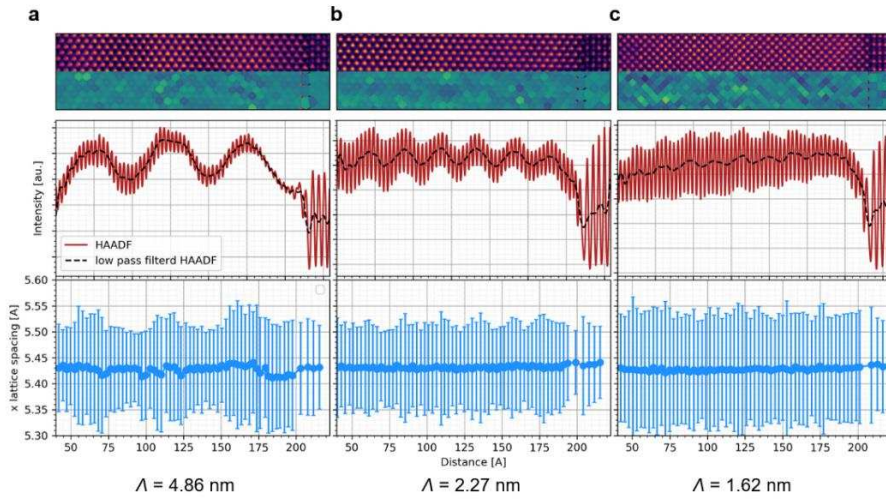
deformation along the b. (100), c. (010), and d. (001) directions. The off-site displacements of the cations result in local-symmetry breaking. Note that replacing one of the ions with Gd will result in a structure with three variants that are equivalent to the distortion of Ceria without Gd.

Supplementary Information

Atomically engineered interfaces yield extraordinary electrostriction

Haiwu Zhang^{1*}, Nini Pryds^{1*}, Daesung Park², Nicolas Gauquelin³, Simone Santucci¹, Dennis V. Christensen¹, Daen Jannis³, Dmitry Chezganov³, Rata Diana⁴, Andrea R. Insinga¹, Ivano E. Castelli¹, Johan Verbeeck³, Igor Lubomirsky⁵, Dragan Damjanovic², and Vincenzo Esposito^{1*}

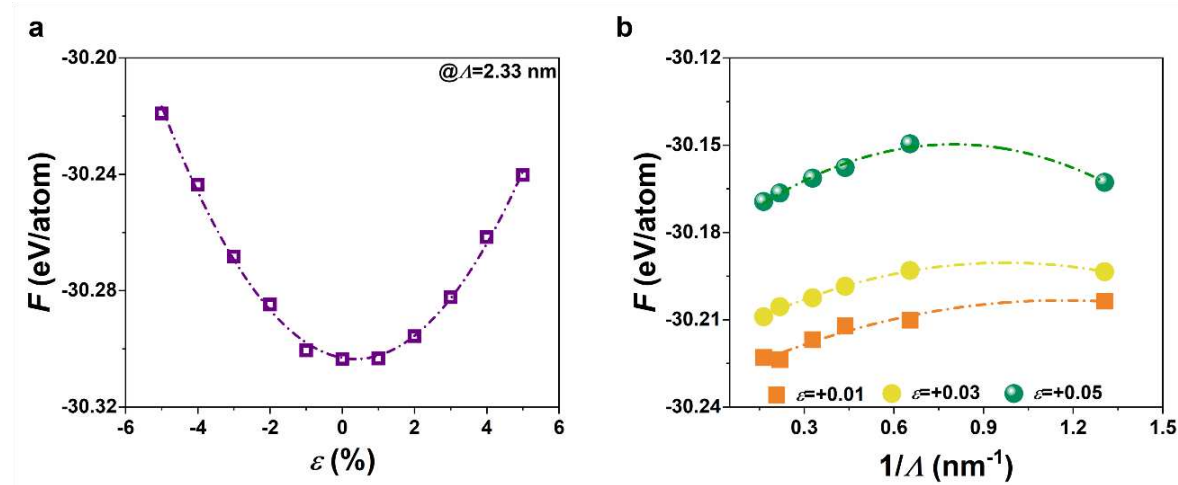
1. Cross-section analysis by HAADF-TEM



Supplementary Fig. 1 | HAADF-TEM analysis along the cross-section of the heterostructures. a. $\Lambda = 4.86$ nm. **b.** $\Lambda = 2.27$ nm. **c.** $\Lambda = 1.62$ nm.

Note that the in-plane lattice parameters of $\text{CGO}/[\text{ESB}/\text{CGO}]_N$ are constant along the cross-section of the heterostructures (blue data points).

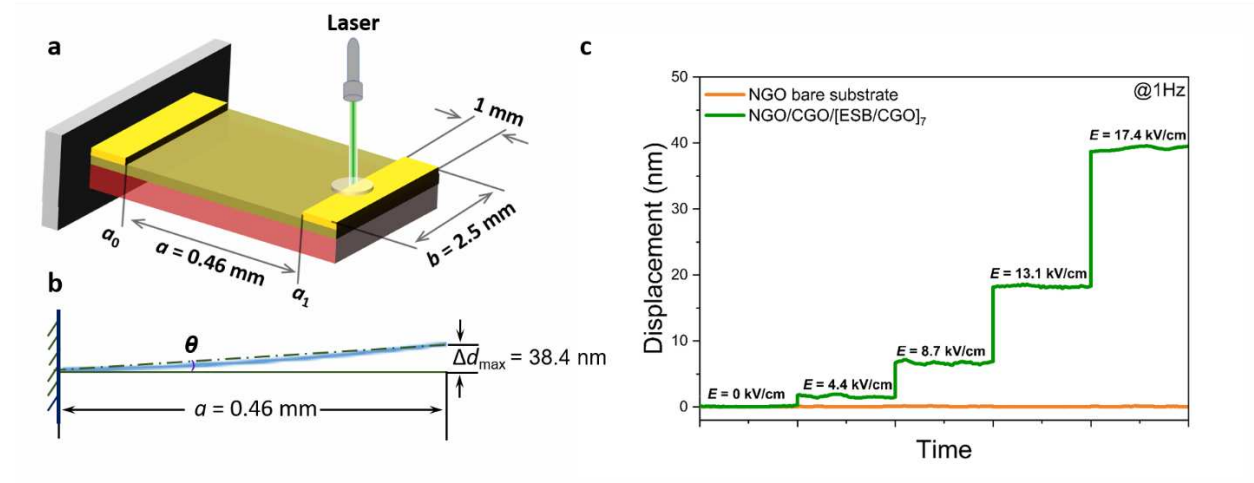
2. Free energy by atomic-scale simulations



Supplementary Fig. 2 | Helmholtz free energy as a function of modulation length and biaxial strain. a. Free energy (F) of heterostructure with a modulation length (Λ) of 2.33 nm. **b.** Free energy as a function of Λ for different biaxial strains (ϵ). The simulations were performed by fixing the in-plane lattice parameters, allowing the out-of-plane lattice parameters to change.

Supplementary Fig. 2a shows the Helmholtz free energy (F) of heterostructure with a modulation length (Λ) of 2.33 nm. The value of F increases with the increase of the biaxial strain. The calculated F for different strain values (without applying an electric field) exhibits a maximum as a function of Λ (Supplementary Fig. 2b), which can be attributed to the lattice distortions caused by the interfacial strain at the CGO/ESB interfaces.

3. Electrostriction measurement



Supplementary Fig. 3 | Electrostriction measurement. **a.** Schematic illustration of the geometry of the cantilever. The displacement along the out-of-plane direction is measured as a function of time under an electric field. **b.** Schematic illustration of the deformation of the cantilever. The blue line denotes the curvature. **c.** Comparison of the displacements of bare NGO₍₁₀₀₎ substrate with NGO/CGO/[ESB/CGO]_N as a function of electric field using the planar electrode configuration.

Supplementary Fig. 3a schematically illustrates the geometry of the cantilever with a planar electrode configuration, with the two electrodes placed on top of the thin films in parallel. This configuration does not require the bottom electrode, thus facilitating the choice of a substrate with the desired lattice mismatch (and therefore, biaxial strain).³⁸

The displacements (Δd) that respond to the electric field at the free end of the cantilever (a_1) were measured. This configuration yields the longitudinal electrostriction coefficient (*i.e.*, M_{33}).³⁸ However, M_{xx} is used for ease of comparison with results taken from the literature. The distance (a) between the two electrodes was 0.46 mm, width (b) was 2.5 mm, and thickness of the NGO substrate was 0.1 mm.

The induced curvature (Δk) is calculated using $\Delta k = 2\Delta d/(a^2)$.³⁹ Subsequently, the in-plane stress is calculated using the well-known Stoney formula³⁹

$$\Delta\sigma = \frac{Y_{\text{sub}}}{1 - \nu_{\text{sub}}} \frac{d_{\text{sub}}^2}{6t_{\text{film}}} \Delta k \quad 1$$

where Y_{sub} is Young's modulus, ν_{sub} is the Poisson ratio, and d_{sub} and d_{film} are the thicknesses of the substrate and film, respectively.

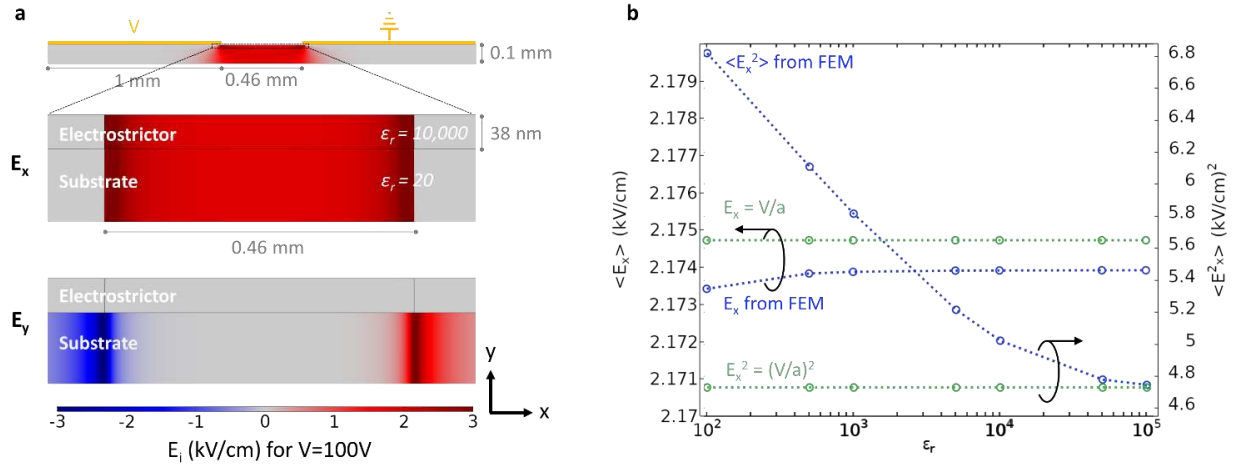
Then, M_{xx} is obtained by linearly fitting the stress ($\Delta\sigma$) against the electric field squared by:

$$M_{xx} = \frac{\Delta\sigma}{E^2 \cdot Y_{film}} \quad 2$$

where Y_{film} is the Young's modulus of the heterostructures, which is taken to be the weighted average of CGO and ESB. The Young's modulus (Poisson ration) for NGO, CGO and ESB are $200.97(0.29)^{40}$, $200(0.33)^{41}$, and $72.8(0.39)^{42}$, respectively.

For NGO/CGO/[ESB/CGO]₇, the maximum displacement is 38.4 nm under the highest electric field ($V/a = 17.4$ kV/cm) at 1 Hz. This configuration yields a deformation of $\Delta d_{max}/a = 38.4 \text{ nm}/0.46 \text{ mm} = 8.35 \times 10^{-5} \ll 1\%$ (Supplementary Fig. 3b), corresponding to an angle change of 0.00478295° ; such a small angle change indicates that the "bending" of the cantilever can be neglected. Supplementary Fig. 3c shows the displacements of the bare NGO₍₁₀₀₎ substrate with the planar electrode configuration; the NGO was not electrostrictive-active. Thus, the contributions associated with high electric fields, such as polarisation or electrostatic forces (*i.e.*, Maxwell stress tensor), can be neglected. This assumption is consistent with the results of Fig. 1c discussed in the main text with the same planar electrode configuration, M_{xx} increases by approximately two orders of magnitude from NGO/CGO to NGO/CGO/[ESB/CGO]₇, which suggests that the variation of the thin film dominates the electromechanical response.

4. Electric field distribution by finite element simulations

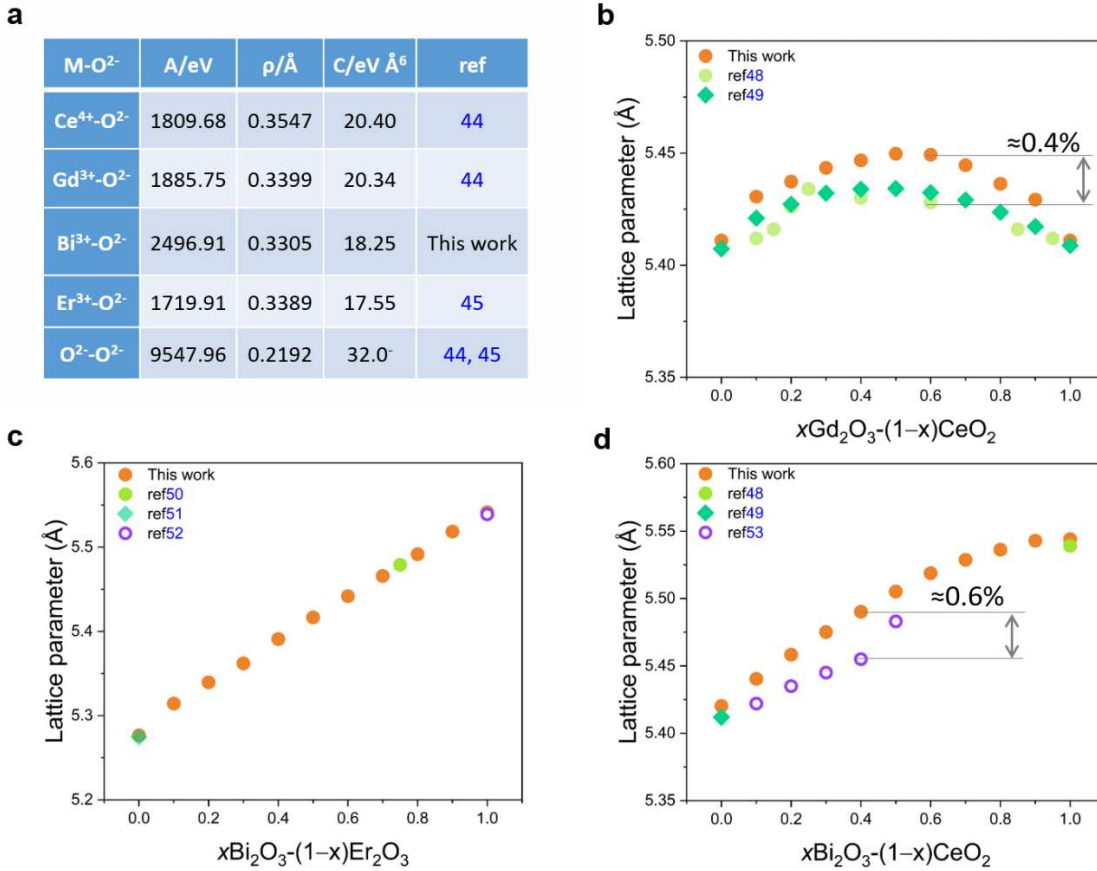


Supplementary Fig. 4 | Electric field distribution by finite element simulations. **a.** Distribution of the X- and Y-components of the electric field (E_x and E_y) in the electrostrictive cantilever and NGO substrate when an electrostatic potential of $V = 100$ V is applied. **b** Average of the electric field and squared electric field as a function of the dielectric constant of the thin film. The average is calculated in the $0.46 \text{ mm} \times 38 \text{ nm}$ region of the electrostrictive film between the electrodes and compared to the naïve prediction where $E_x = V/a$. Note that the dielectric displacement field is channelled by the high dielectric constant materials, i.e., CGO.

Finite element modelling (FEM) was performed to account for the electric field distribution, according to the procedure described by Nigon *et al.*³⁸. Here, the electric field distribution was calculated using a 2D model of the cantilever geometry in Supplementary Fig. 3a. A grounded electrode and a biased electrode were placed on top of the thin film deposited on the NGO substrate. The cantilever was further surrounded by air at the top and bottom. The deposited superlattice was modelled as a single dielectric layer. A custom mesh was created to account for the high aspect ratio of the thin films. The average electric field in the thin film was invariant to its thickness in the probed range ($38 \leq d_{film} \leq 80 \text{ nm}$). The electric field distribution is shown in Supplementary Fig. 4a; E_x is the dominant component in the film, which is consistent with previous studies.^{38, 43} The electric field was fairly constant in the majority of the electrostrictor ($E_x = 0$ below the electrodes and $E_x \sim V/a$ between the electrodes), with the only significant inhomogeneities observed close to the edge of the electrodes; E_x increased from 0 below the electrodes, encountered a peak, and decreased to a constant value. The average of E_x and E_x^2 as a function of the dielectric constant of the electrostrictor is shown in Supplementary Fig. 4b. For all probed dielectric constants, the average E_x can be approximated well by $E_x \approx V/a$. However, for low dielectric constants, the peak in E_x close to the electrode edge increases, increasing the average of E_x^2 . However, the thinner the film with respect to the electrode distance, the lower

the impact of the region close to the electrode. The geometry and high dielectric constant of the electrostrictive heterostructure used here ensure that $E_x \approx V/a$ and $E_x^2 \approx (V/a)^2$ are fair approximations and are used in the following for convenience.

5. Atomic-scale simulations



Supplementary Fig. 5 | Potential parameters and ground-state structural properties. **a**, Table showing the short-range Buckingham potential parameters. More details about the potential parameters for other systems shown in Extended Data Figure 6 were taken from refs. 46 and 47. **b**, **c**, and **d**, comparison of calculated and experimental lattice parameters for $x\text{Gd}_2\text{O}_3-(1-x)\text{CeO}_2$ (**b**), $x\text{Er}_2\text{O}_3-(1-x)\text{Bi}_2\text{O}_3$ (**c**), and $x\text{Bi}_2\text{O}_3-(1-x)\text{CeO}_2$ (**d**). The maximum difference between the calculated values and experimental values is $\sim 0.4\%$ for $x\text{Gd}_2\text{O}_3-(1-x)\text{CeO}_2$ and $\sim 0.6\%$ for $x\text{Bi}_2\text{O}_3-(1-x)\text{CeO}_2$. The lattice parameters for $x\text{Gd}_2\text{O}_3-(1-x)\text{CeO}_2$ were taken from refs 48, 49. The lattice parameters for Bi_2O_3 , Er_2O_3 and $\text{Er}_{0.8}\text{Bi}_{1.2}\text{O}_3$ were taken from Ref 50, 51, and 52. The lattice parameters for $x\text{Bi}_2\text{O}_3-(1-x)\text{CeO}_2$ were taken from Ref 53 (open circles).

The Buckingham potential parameters for ceria employed in the current study were developed by Minervini *et al.*⁴⁴ They have already been validated extensively and can describe the lattice parameter, elastic constants, thermal expansion coefficient, heat capacity, defect formation energies, and defect-dislocation interactions.⁴⁵

The potential parameters are adequate to model the nonlinear variation of the CGO lattice parameter as a function of the dopant concentration (Supplementary Fig. 5b). Supplementary Fig. 5c and d further show that the calculated lattice

parameters of $x\text{Bi}_2\text{O}_3-(1-x)\text{Er}_2\text{O}_3$ and $x\text{Bi}_2\text{O}_3-(1-x)\text{CeO}_2$ are consistent with previous experimental results for $\delta\text{-Bi}_2\text{O}_3$, Er_2O_3 , and their solid solutions.⁴⁸⁻⁵³ The pressure is maintained at 1.01325 bar to simulate such solid solutions.

The steps for the molecular dynamics simulations are listed below. 1) Construct the $(100) \times (0\bar{1}1) \times (011)$ -orientated heterostructures with various modulation lengths; 2) introduce the dopants and oxygen vacancies at random; 3) apply biaxial strains by adjusting the in-plane lattice parameters to specific values; 4) equilibrate at 2400 K for 600 ps, followed by another equilibration at 300 K for 300 ps; 5) turn on the electrical field along the (100) -crystallographic direction at 300 K and extract the optimised structures after 100 ps.

Large supercells were used to account for the various possible distributions of the point defects within the heterostructures: $10 \times 8\sqrt{2} \times 24\sqrt{2}$ (41472 atoms) and $16 \times 12\sqrt{2} \times 12\sqrt{2}$ (49768 atoms) were used to model the interlayer interaction (Fig. 3) and the electrostriction coefficient (Fig. 4b), respectively. The position of the cationic planes was determined by averaging the position of the cations within each layer, based on which cationic interplanar distance (d_c) was calculated. The chemical formulae were $\text{Ce}_{6144}\text{Gd}_{1536}\text{O}_{14592}/\text{Bi}_{6144}\text{Er}_{1536}\text{O}_{11520}$, and $\text{Ce}_{7376}\text{Gd}_{1840}\text{O}_{17512}/\text{Bi}_{7376}\text{Er}_{1840}\text{O}_{13824}$, corresponding to the experimental compositions of $\text{Ce}_{0.8}\text{Gd}_{0.2}\text{O}_{1.9}$ and $\text{Er}_{0.4}\text{Bi}_{1.6}\text{O}_3$, respectively. Thus, various distributions of defects and their responses to the electric field were included in the model and were captured by the generated dipoles. The pressure was maintained at 0.0 bar for the simulation of heterostructures.

6. Phenomenological simulations.

To evaluate the effect of the volumetric strain observed experimentally, we investigate the electrostriction as a function of volumetric strain ($\Delta V/V$) by considering a model based on the energy of elastic and electric dipoles. This model considers an ensemble of elastic dipoles, where the elastic dipole moment is rigidly connected to an electric dipole. We assume that the elastic-electric dipole interacts with an initial strain field and external electric field by changing its orientation in space. The equilibrium orientation is the one that minimises the sum of the elastic and electric interaction energies.

We denote the electric dipole vector and elastic dipole tensor by \mathbf{p} and $\bar{\Sigma}$, respectively, and their components by p_j and Σ_{ij} , respectively. We assume that the electric and elastic dipoles rotate together. This assumption is consistent with the recent analysis of electrical and electrical dipoles formation in oxygen defective cerium oxide proposed by Das *et al.*²⁹ Denoting the components of the rotation matrix as R_{ij} , we have:

$$\begin{cases} p'_i = R_{ij}p_j \\ \Sigma'_{ij} = R_{ik}R_{jh}\Sigma_{kh} \end{cases} \quad 3$$

where the Einstein summation convention is adopted. The rotation is parametrised by three angles, $\{\alpha_1, \alpha_2, \alpha_3\}$, for example, the Euler angles. We minimise the total energy of the system with respect to these angles. The total energy is

$$E_{\text{total}} = E_{\text{elastic}} + E_{\text{electric}} \quad 4$$

where E_{elastic} and E_{electric} are the elastic and electric contributions, respectively.

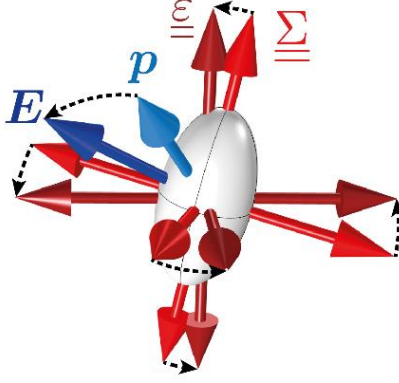
Written in terms of their components, the interaction energy between the elastic point dipole Σ'_{ij} and the strain field ε_{ij} is:⁵⁴

$$E_{\text{elastic}} = -\Sigma'_{ij}\varepsilon_{ij} \quad 5$$

Likewise, the interaction energy between the electric point-dipole p'_i and the external electric field E_i is:

$$E_{\text{electric}} = -p'_i E_i \quad 6$$

The dipoles will assume the orientation associated with the minimum total energy, which corresponds to minimising E_{total} with respect to the angles $\{\alpha_1, \alpha_2, \alpha_3\}$. This configuration is illustrated in Supplementary Figure 6.



Supplementary information Fig. 6 | Schematic illustration of the coupling between electric and elastic dipoles. The symbols, $\bar{\Sigma}$, p , $\bar{\epsilon}$, and E denote elastic dipole, electric dipole, strain field and electric field, respectively. Note that the external electric field polarises the electric dipole. The reorientation of the electric dipole is accompanied by the reorientation of the elastic dipole, which generates field-induced strain.

We thus obtain the electric dipole \mathbf{p}_{eq} and elastic dipole $\bar{\Sigma}_{\text{eq}}$ corresponding to the minimum energy equilibrium orientation. We then consider the average electric polarisation \mathbf{P} and average mechanical stress $\bar{\sigma}$ associated with the electric-elastic dipoles:

$$\begin{cases} \mathbf{P} = \rho_{\text{dipoles}} \mathbf{p}_{\text{eq}} \\ \bar{\sigma} = \rho_{\text{dipoles}} \bar{\Sigma}_{\text{eq}} \end{cases} \quad 7$$

where ρ_{dipoles} is the volume density of dipoles (i.e. number of dipoles per unit volume). We now compute the electric susceptibility tensor $\bar{\chi}$ from the relation

$$\mathbf{P} = \epsilon_0 \bar{\chi} \mathbf{E} \quad 8$$

where ϵ_0 denotes the vacuum permittivity. Here, since the electric field \mathbf{E} has been applied along the x direction, we will obtain the first column of $\bar{\chi}$ (which is a symmetric tensor). In order to obtain the electrostrictive coefficients from $\bar{\chi}$ and $\bar{\sigma}$, we need to apply the following relation^{55, 56}:

$$M_{ijkl} = \left(\frac{\epsilon_0}{2}\right) \left(\frac{d\chi_{ij}}{d\sigma_{kl}}\right)_E \quad 9$$

where the subscript E indicates that the derivative must be evaluated for constant electric field E . To apply the previous equation, we must evaluate the relation between stress and electrical susceptibility while varying the relative strength between the elastic and electric interaction. Therefore, we evaluate the variation of $\bar{\chi}$ and $\bar{\sigma}$ by performing a re-scaling by a factor γ of the original elastic dipole given as input:

$$\bar{\Sigma} \rightarrow \gamma \bar{\Sigma} \quad 10$$

This re-scaling corresponds to changing the strength of the elastic dipole. We now repeat the same procedure for calculating $\bar{\chi}$ and $\bar{\sigma}$. Since the elastic energy is proportional to γ , the re-scaling changes the trade-off between the elastic and electric energy, therefore changing the solution. In this way, we obtain the following solutions as a function of γ :

$$\bar{\chi} = \bar{\chi}(\gamma) \text{ and } \bar{\sigma} = \bar{\sigma}(\gamma) \quad 11$$

From the resulting curve $\chi_{xx}(\sigma_{xx})$ we consider the limit for which the electrical interaction is dominating, i.e. $\gamma \rightarrow 0$, and evaluate the derivative in this limit. Since we are interested in the coefficient M_{xxxx} , we will use the following relation:

$$M_{xxxx} = \left(\frac{\epsilon_0}{2}\right) \left(\frac{d\chi_{xx}}{d\sigma_{xx}}\right)_E \quad 11$$

The electrostrictive coefficient M_{xxxx} (shortened as M_{xx}) is then calculated in this way for different values of the out of plane strain ϵ_{zz} , corresponding to different values of the volumetric strain ($\Delta V/V$) to generate a relation between M_{xx} and ($\Delta V/V$).

As indicated in ref 29, we assume the following expression for the elastic dipole tensor:

$$\bar{\Sigma} = \begin{pmatrix} -9.633 & 0.001 & 0.001 \\ 0.001 & -9.633 & 1.734 \\ 0.001 & 1.734 & -9.633 \end{pmatrix}$$

Moreover, we assume the following inputs:

$$\bar{\epsilon} = \begin{pmatrix} 1\% & 0 & 0 \\ 0 & 1\% & 0 \\ 0 & 0 & \epsilon_{zz} \end{pmatrix}; \mathbf{E} = \begin{pmatrix} 1 \\ 0 \\ 0 \end{pmatrix}; \mathbf{p} = 10^{-5} \begin{pmatrix} 0 \\ 2 \\ 0 \end{pmatrix};$$

The resulting curve of the electrostrictive coefficient M_{xx} as a function of $\Delta V/V$ is shown in Fig. 4a

It is important to stress that when the density of defects is sufficiently low (as it is in the case considered here), it is a justifiable assumption to consider the dipoles as independent. Instead, when the density of defects is high, it is necessary also to include the dipole-dipole nearest-neighbour interaction terms. The elastic and electric nearest-neighbour interaction energies have a form analogous to that of the Ising/Heisenberg model, and they can be expressed as:

$$E_{elastic-elastic} = J_{elastic} \sum_{\langle h,k \rangle} \Sigma_{ij}^h \Sigma_{ij}^k \quad 13$$

$$E_{electric-electric} = J_{electric} \sum_{\langle h,k \rangle} p_i^h p_i^k \quad 14$$

Here $J_{elastic}$ and $J_{electric}$ are the interaction strengths coefficients, the superscript indexes h and k indicate specific dipole locations in the lattice, and the notation $\langle h, k \rangle$ indicates that the summation only runs among nearest-neighbour dipoles. Depending on the signs of $J_{elastic}$ and $J_{electric}$, these interaction terms promote aligned or anti-aligned configurations.

However, our simple non-interacting dipoles model can produce results that agree with the trend observed experimentally and provide an intuitive explanation for the mechanism behind the enhanced electrostriction. Hence, we decided not to include these terms in our calculations, which is a realistic assumption given the low spatial density of defects.

References

38. Nigon, R., Raeder, T. M., Mural, P. Characterization methodology for lead zirconate titanate thin films with interdigitated electrode structures, *J. Appl. Phys.* **121**, 204101 (2017).
39. Mazzalai, A. et al, Characterisation and fatigue of the converse piezoelectric effect in PZT films for MEMS applications, *J. Microelectromech. Syst.* **24**, 831-838 (2015).
40. <https://materialsproject.org/materials/mp-3196/>.
41. Morales, M. et al, Mechanical properties at the nanometer scale of GDC and YSZ used as electrolytes for solid oxide fuel cells, *Acta Mater.* **58**, 2504-2509 (2010).
42. <http://progs.coudert.name/elate/mp?query=mp-22891>.
43. Nguyen, C. H. et al, Probing-models for interdigitated electrode systems with ferroelectric thin films, *J. Phys. D: Appl. Phys.* **51** (2018).
44. Minervini, L., Grimes, R. W., Sickafus, K. E. Disorder in pyrochlore oxides, *J. Am. Ceram. Soc.* **83**, 1873-1878 (2000).
45. Vyas, S., Grimes, R. W., Gay, D. H., Rohl, A. L. Structure, stability and morphology of stoichiometric ceria crystallites, *Faraday Trans.* **94**, 427-434 (1998).
46. De Souza, R. A. Maier, J. A computational study of cation defects in LaGaO₃, *Phys. Chem. Chem. Phys.* **5**, 740-

748 (2003).

47. Zacate, M. O. Grimes, R. W. Predicted calcium titanate solution mechanisms in calcium alumioferrite and related phases, *J. Mater. Sci.* **35**, 3727-3732 (2000).

48. Kossoy, A. et al. Evolution of the local structure at the phase transition in CeO₂-Gd₂O₃ solid solutions, *Phys. Rev. B.* **87**, 054101 (2013).

49. Artini, C., et al, Structural characterisation of the CeO₂/Gd₂O₃ mixed system by synchrotron X-ray diffraction, *J. Solid State Chem.* **190**, 24-28 (2012).

50. Battle, P. D., Catlow, C. R. A., Moroney, L. M. Structural and dynamical studies of δ -Bi₂O₃ oxide-ion conductors II, *J. Solid State Chem.* **67**, 42-50 (1987).

51. Heiba, Z. K., Mohamed, M. B., Fuess, H. Effect of Mn doping on structural and magnetic susceptibility of C-type rare earth Nano oxides Er_{2-x}Mn_xO₃, *Mater. Res. Bull.* **47**, 4278-4282 (2012).

52. Begemann, B., Jansen, M. Bi₄O₇, das erste definierte binÄre Bismut(III, V)-Oxid. *Less Comm. Metal.* **156**, 123-135 (1989).

53. Sardar, K. et al. Nanocrystalline cerium-bismuth oxides: Synthesis, structural characterisation, and redox properties, *Chem. Mater.* **22**, 6191-6201 (2010).

54. Dudarev, S. L., Ma, P.-W. Elastic fields, dipole tensors, and interaction between self-interstitial atom defects in bcc transition metals, *Phys. Rev. Materials.* **2**, 033602 (2018).

55. Newnham, R. E., Sundar, V., Yimmirun, R., Su, J., Zhang, Q. M. Electrostriction: Nonlinear Electromechanical Coupling in Solid Dielectrics, *J. Phys. Chem. B.* **101**, 10141-10150 (1997).

56. Eury, S., et al. Converse electrostriction in polymers and composites, *Mater. Chem. Phys.* **61**, 18-23 (1999).